3. Oxidation and Corrosion of Alloys

- a. Review of thermodynamic principles
- Review of diffusion principles Point Defects in Metals and Oxides
- c. Oxide stoichiometry and defect chemistry
 - Anionic and cationic diffusion
 - Defect chemistry modification
 - Stoichiometry and growth
 - Stoichiometry and electrical conduction

Oxidation and Corrosion of Alloys (continued)

- d. Principles of oxidation and corrosion
 - Parabolic and transition from parabolic
 - External vs. internal oxidation (Selective oxidation)
 - Oxide adherence
 - Environmental influences in hydrogen fueled SOFCs (Evaporation, H2O content, dual-atmosphere, pressure, current density, breakaway corrosion...)
 - Corrosion mechanisms using complex fuels (Oxidation in multi component gases, Carburization, sulfidation, deposit effects)
 - Interaction between adjacent SOFC components

Thermodynamic Principles

$$G' = H' - TS'$$

At constant temperature and pressure:

 $\Delta G' < 0$ spontaneous reaction expected

 $\Delta G' = 0$ equilibrium

 $\Delta G' > 0$ thermodynamically impossible process

$$aA + bB = cC + dD$$

$$\Delta G' = \Delta G^{\circ} + RT \ln \left(\frac{a_C^c a_D^d}{a_A^a a_B^b} \right)$$

$$a_i = \frac{p_i}{p_i}$$

$$\Delta G^{o} = c\Delta G_{C}^{o} + d\Delta G_{D}^{o} - a\Delta G_{A}^{o} - b\Delta G_{B}^{o}$$

At equilibrium:

$$\Delta G^{\circ} = -RT \ln \left(\frac{a_C^c a_D^d}{a_A^a a_B^b} \right)_{eq} = -RT \ln K$$

Note: Free energy of formation data can be accessed either directly or as "Log $K_{P.}$ The latter allows direct calculation of the equilibrium constant for the overall reaction.

Calculation of Activities in a Gaseous Environment

Problem A gas consisting of 60 vol % H₂ and 40 vol% CO₂ is let into a reaction chamber and heated to 1200K at a total pressure of 1 atm. Calculate the oxygen partial pressure and carbon activity in this gas when it comes to equilibrium.

Solution The common species which can form in such a gas mixture and their $\log K_P$ values at 1200K are listed in the following table.

<u>Species</u>	$log K_{P}$
CO_2	$17.24\overline{3}$
CO	9.479
H_2O	7.899
$\overline{\mathrm{H}_{2}}$	0.00

$$H_2(g) + CO_2(g) = H_2O(g) + CO(g)$$

$$\log K_R = \log K_P^{H_2O} + \log K_P^{CO} - \log K_P^{CO_2} = 0.135$$

$$K_R = 1.365 = \frac{p_{H_2O} p_{CO}}{p_{H_2} p_{CO_2}}$$

$$p_i = \frac{n_i}{n_{tot}} P_{tot}$$

$$K_R = 1.365 = \frac{n_{H_2O}n_{CO}}{n_{H_2}n_{CO_2}}$$

$$K_R = 1.365 = \frac{\lambda \lambda}{(0.6 - \lambda)(0.4 - \lambda)}$$
 $\lambda = 0.2575$ moles.

<u>Species</u>	Final Comp. (moles)	Partial Pressures (atm)
H_2	0.3425	0.3425
$\overline{\mathrm{CO}}_2$	0.1425	0.1425
$\overline{\text{CO}}$	0.2575	0.2575
H_2O	0.2575	0.2575

Calculation of Activities

Oxygen Partial Pressure

$$H_2(g) + 1/2O_2(g) = H_2O(g)$$

$$K_P = 7.924x10^7 = \frac{p_{H_2O}}{p_{H_2O}p_{O_2}^{1/2}} = \frac{0.2575}{0.3425p_{O_2}^{1/2}}$$

$$p_{O_2} = 9.0x10^{-18} atm$$

Carbon Activity

$$2CO(g) = CO_{2}(g) + C(s)$$

$$\log K_{R} = \log K_{P}^{CO_{2}} - 2\log K_{P}^{CO} = -1.715$$

$$K_{R} = 0.193 = \frac{p_{CO_{2}}a_{C}}{p_{CO}^{2}} = \frac{0.1425a_{C}}{(0.2575)^{2}}$$

$$a_{C} = 0.009$$

Will this gas oxidize Ni or Cr?

$$Ni(s) + \frac{1}{2}O_2(g) = NiO(s)$$

$$Log K_{p} = 5.75$$

$$K_P = \frac{1}{p_{O_2}^{\frac{1}{2}}} = 5.6x10^5$$

$$p_{O_2}^{eq} = 3.2x10^{-12} atm$$

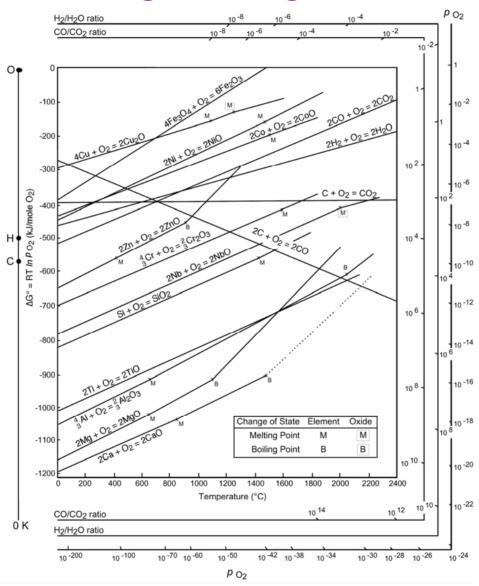
Ni cannot oxidize

$$2Cr(s) + \frac{3}{2}O_2(g) = Cr_2O_3(s)$$

$$p_{O_2}^{eq} = 1.2x10^{-24} atm$$

Cr will tend to oxidize

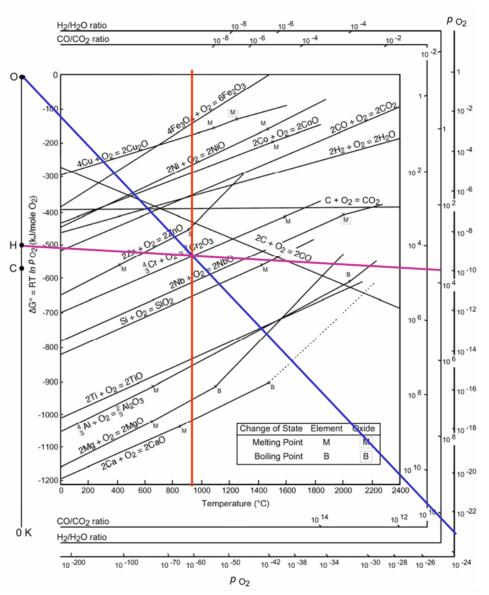
Ellingham Diagram



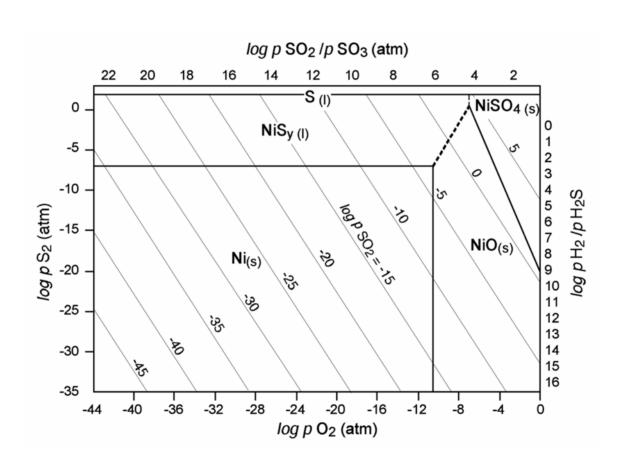
Ellingham Diagram

$$p_{O_2} = 9.0x10^{-18} atm$$

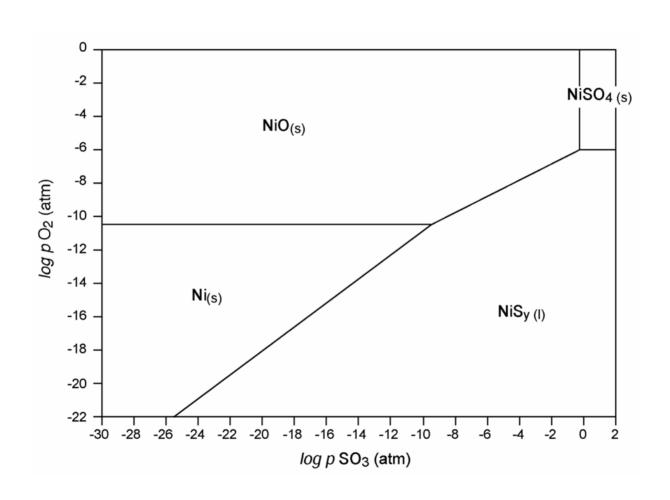
$$\frac{p_{H_2}}{p_{H_2O}} = 1.33$$



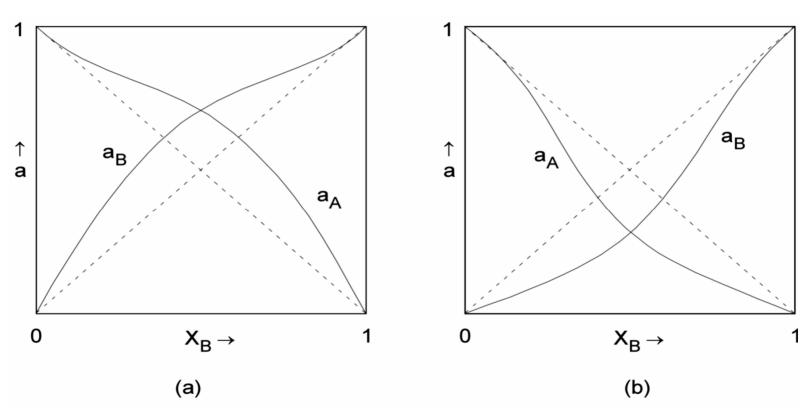
Isothermal Stability Diagram Ni-S-O System, 1250K



Isothermal Stability Diagram Ni-S-O System, 1250K



Solution Thermodynamics



Positive Deviation from Ideality

Negative Deviation from Ideality

Solution Thermodynamics

$$a_i = N_i$$
 Ideal Solution

$$a_i = \gamma_i N_i$$
 Real Solution, $\gamma_i = f(N_i)$

$$a_i = \gamma_i(\infty)N_i$$
 Dilute Solution, $\gamma_i(\infty) = constant$

Sievert's Law

Consider Hydrogen Dissolving into Nickel

$$\frac{1}{2}H_2(g) = \underline{H}(inNi)$$

$$K = \frac{a_H}{p_{H_2}^{1/2}} = \frac{\gamma_H(\infty)N_H}{p_{H_2}^{1/2}}$$

$$N_H = \frac{K}{\gamma_H(\infty)} p_{H_2}^{1/2} = k_S p_{H_2}^{1/2}$$

Chromia Evaporation

$$Cr_2O_3(s) + \frac{3}{2}O_2(g) = 2CrO_3(g)$$

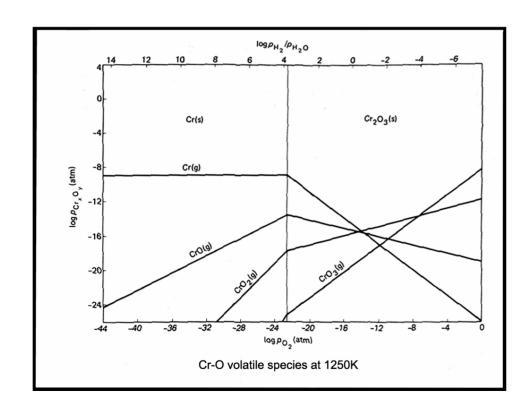
$$p_{cro_3} = K^{\frac{1}{2}} a_{cr_2O_3}^{\frac{1}{2}} p_{O_2}^{\frac{3}{4}}$$

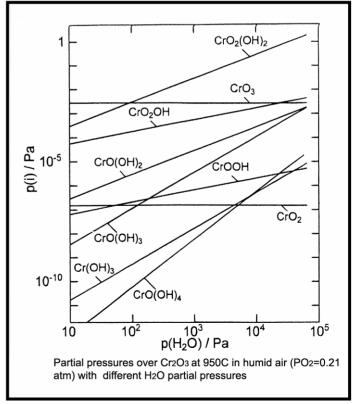
CHROMIA

• At high T and high PO₂ volatile oxides develop

$$Cr_2O_3 + 3/2 O_2 \rightarrow 2 CrO_3(g)$$

 $Cr_2O_3 + 2 H_2O + 3/2 O_2 \rightarrow 2 CrO_2(OH)_2$

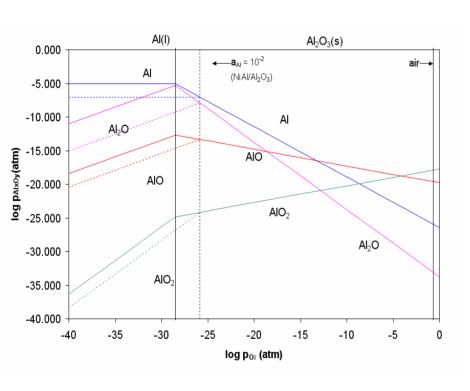


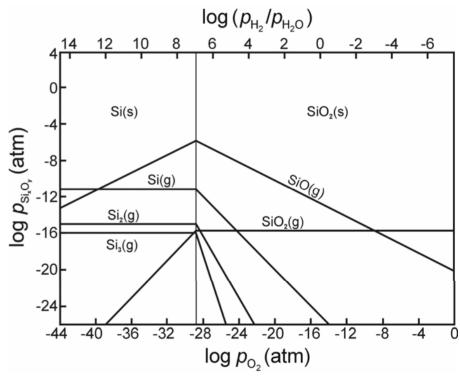


Vapor Species Diagrams for the Al-O and Si-O Systems

AI - O 1473K

Si - O 1250K





Diffusion Fundamentals

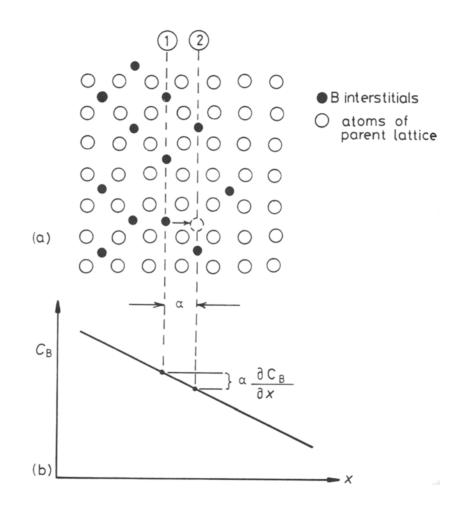
$$J_B = -\widetilde{D} \frac{\partial C_B}{\partial x}$$
 Fick's First law

$$\frac{\partial C_B}{\partial t} = \widetilde{D} \frac{\partial^2 C_B}{\partial x^2}$$
 Fick's Second Law

Diffusion of Interstitial Atoms (e.g. H, C) in a Metal

$$J_B = -\widetilde{D} \frac{\partial C_B}{\partial x}$$

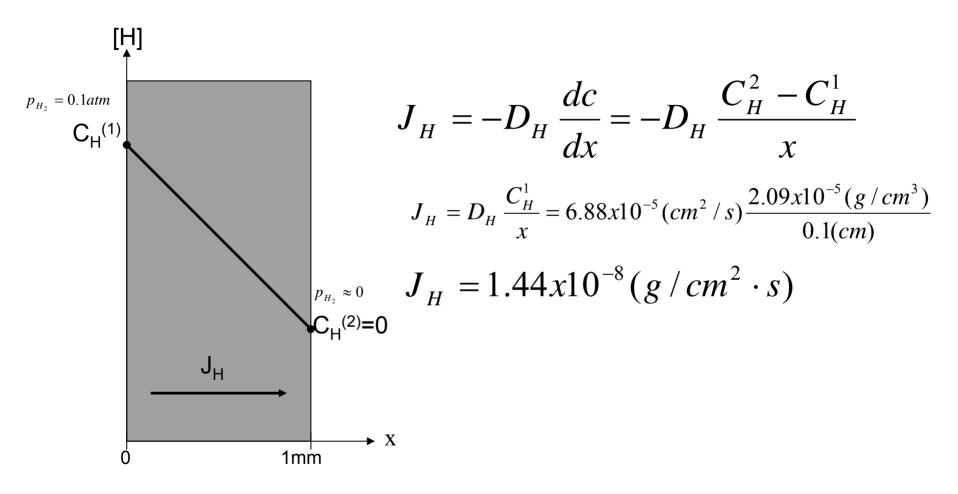
$$\frac{\partial C_B}{\partial t} = \widetilde{D} \frac{\partial^2 C_B}{\partial x^2}$$



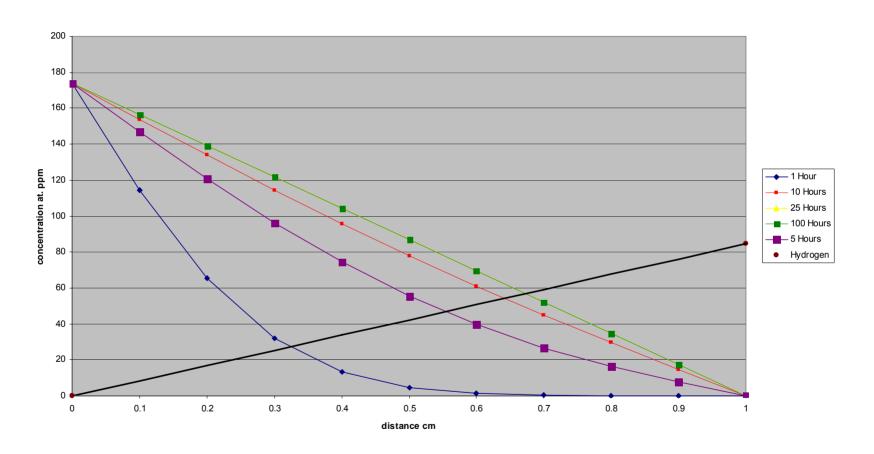
Fick's First Law

Steady-State Flux of Hydrogen Through Nickel

Steady State Diffusion of H₂ Through Ni T=800°C

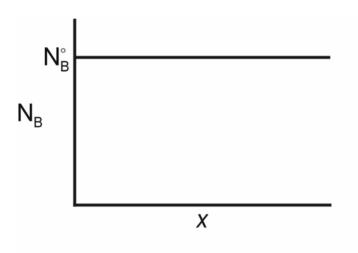


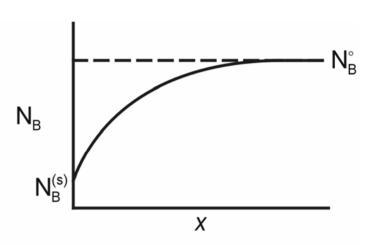
Oxygen and Hydrogen Concentration Profiles in Nickel



Fick's Second Law

Concentration Profile for a Solute B Being Lost by Evaporation





a.

b.

$$\frac{\partial N_B}{\partial t} = \widetilde{D} \frac{\partial^2 N_B}{\partial x^2}$$

Boundary Conditions: At time t: $N_B = N_B^{(S)}$ at x = 0

$$N_B = N_B^{\circ}$$
 at $x = \infty$

$$Z = \frac{x}{2\sqrt{\widetilde{D}t}}$$

$$\frac{-x}{\sqrt{\widetilde{D}t^3}} \frac{dN_B}{dZ} = \frac{1}{t} \frac{d^2 N_B}{dZ^2}$$

$$y \equiv \frac{dN_B}{dZ}$$

$$y = -\frac{\sqrt{\widetilde{D}t}}{x} \frac{d^2 N_B}{dZ^2} = -\frac{1}{2Z} \frac{d^2 N_B}{dZ^2}$$

$$y = -\frac{1}{2Z} \frac{dy}{dZ}$$

$$-2ZdZ = \frac{dy}{y}$$

$$-Z^2 = \ln y - \ln A$$

$$\frac{dN_B}{dZ} = A \exp(-Z^2)$$

Boundary Conditions: At time t: $N_B = N_B^{(S)}$ at Z = 0

 $N_B = N_B^{\circ}$ at $Z = \infty$

$$\int_{N_B^{(S)}}^{N_B^o} dN_B = A \int_0^{\infty} \exp(-Z^2) dZ$$

R.H. Integral =
$$\frac{\sqrt{\pi}}{2}$$

$$A = \frac{2}{\sqrt{\pi}} \left(N_B^o - N_B^{(S)} \right)$$

$$\int_{N_B^o}^{N_B} dN_B = \frac{2(N_B^o - N_B^{(S)})}{\sqrt{\pi}} \int_{\infty}^{Z} \exp(-Z^2) dZ$$

$$N_B - N_B^o = -\frac{2(N_B^o - N_B^{(S)})}{\sqrt{\pi}} \int_Z^\infty \exp(-Z^2) dZ = -(N_B^o - N_B^{(S)}) erfc(Z)$$

$$\frac{N_B - N_B^o}{N_B^S - N_B^o} = erfc(Z)$$

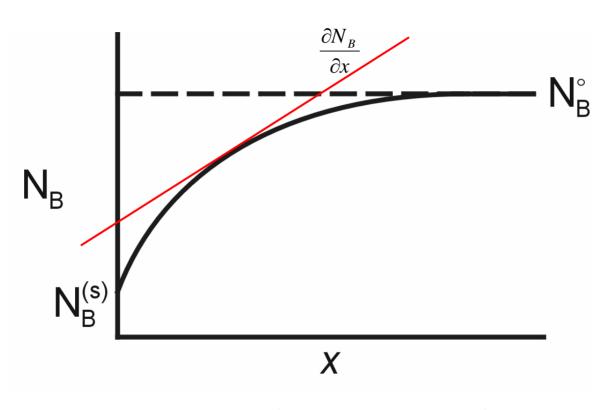
$$\frac{N_B - N_B^{(S)}}{N_B^o - N_B^{(S)}} = erf(Z)$$

$$N_B = N_B^{(S)} + (N_B^o - N_B^{(S)}) erf\left(\frac{x}{2\sqrt{\widetilde{D}t}}\right)$$

General Solution

$$N_B = A_1 + B_1 erf\left(\frac{x}{2\sqrt{Dt}}\right)$$

Calculation of Local Flux



$$J_{B} = -\widetilde{D} \frac{\partial C_{B}}{\partial x} = -\widetilde{D} V_{m} \frac{\partial N_{B}}{\partial x}$$

Oxide Chemistry

Point Defects in Metals

• Point defects are thermodynamically stable because they lower the free energy of the system by significantly affecting the entropy of the system. The important point defects in the metals are:

Vacancies
Interstitials
Divancies
Foreign atoms
Associated complexes of the above

The equilibrium concentration of the defects is obtained by minimizing the free energy and is given by,

$$C_d = \frac{n}{N} = \exp(-\frac{\Delta H_{Form}^d}{kT}) \exp(\frac{\Delta S_{Form}^d}{k})$$

where:

 C_d = concentration of defcts n = number of defects N = number of lattice sites ΔH^d_{Form} = Enthalpy or energy to form defects ΔS^d_{Form} = Entropy of formation of defects

• Estimation of ΔS_{Form}^d is obtained by considering vibrational entropy of crystal and treating atoms as harmonic oscillators.

Defect Motion in Metals:

$$w_{d}\left(\frac{jumps}{\sec}\right) = ve^{\frac{\Delta S_{m}^{d}}{k}}e^{\frac{-\Delta H_{m}^{d}}{kt}}$$

$$D_{d} = \frac{\alpha^{2}}{6}ve^{\frac{\Delta S_{m}^{d}}{k}}e^{\frac{-\Delta H_{m}^{d}}{kT}}$$

$$W_{atom} = C_{d}ZW_{d}$$

$$D_{atom} = \frac{\alpha^{2}}{6}W_{atom} = \frac{\alpha^{2}}{6}C_{d}ZW_{d}$$

$$D_{atom} = \frac{\alpha^{2}}{6}Zve^{\frac{(\Delta S_{F}^{d} + \Delta S_{m}^{d})}{k}}e^{\frac{(\Delta H_{F}^{d} + \Delta H_{m}^{d})}{kT}}$$

 D_{atom} is an ideal diffusion coefficient or tracer diffusion coefficient. In an alloy AB where γ_a is the activity coefficient of A, C_A the concentration of A, and N_A and N_B are mole fractions.

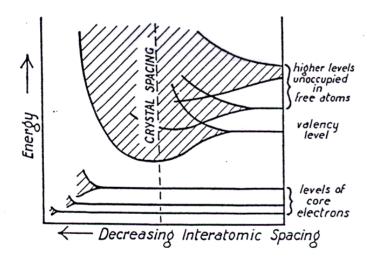
Intrinsic diffusion coefficient:
$$D_A = D_{atomA}^{ideal} \left(1 + \frac{\delta \ln \gamma_A}{\delta \ln C_A} \right)$$

Interdiffusion coefficient:
$$D = N_B D_A + N_A D_B$$

Point Defects on Elemental Semiconductors

The important point defects in elemental semiconductors are:

- Vacancies
- Interstitials
- Foreign atoms
- Electrons
- Holes
- Charge defects involving the above
- Vorious associated complexes of the above

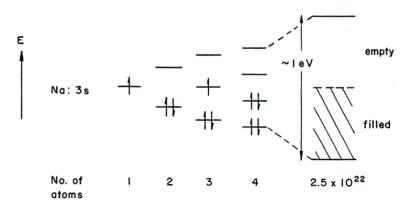


Broadening of atomic energy levels when atoms approach to form a crystal

Important Electron Theory Concepts

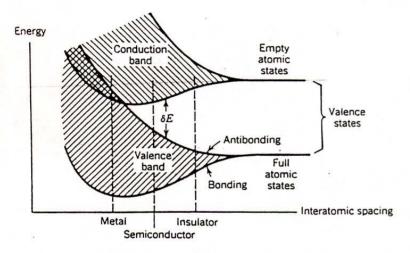
Concepts of Discrete Energy States

Schematic energy diagram showing the energy of all the atoms in a condensed material at various interatomic spacings. At large atomic spacings the energy levels are discrete, but as the atoms come closer together there is interaction between the atoms which result in splitting of energy levels. The total number of electronic states in a system derives directly from the electronic states of the component atoms and must be conserved.

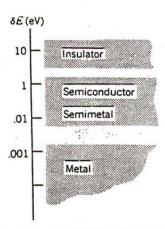


Development of an energy band from the 3s electrons of sodium.

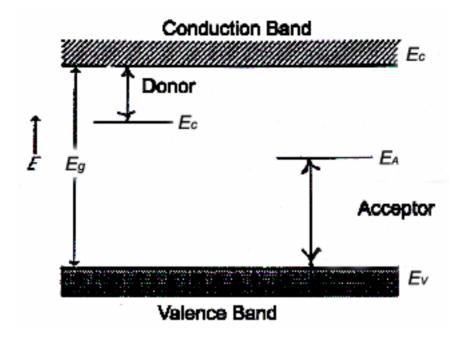
Depending on the atomic spacing and the configuration of the bands, we can have a metal, semiconductor or an isulator.



Electronic energies for a solid as a function of interatomic spacing. At large spacings, all solids show an atomic limit and at small spacings all show a metallic limit (see the text for some qualifications).



The energy needed to raise a solid to electronically excited state, showing ranges of val-corresponding to metals, semiconductors, and sulators at normal temperatures.



Intrinsic and Extrinsic Elemental Semiconductors

Intrinsic:
$$n = p = K_i^{\circ} e^{-\frac{E_g}{2bT}}$$
Extrinsic: $np = K_i^{\circ} e^{-\frac{E_g}{bT}}$

Extrinsic:
$$np = K_i^{\circ} e^{-\frac{L_g}{bT}}$$

-ionized native defects and dopants

Electrons Acceptors Conduction band 0.6 10 22 0.2 300 200 7()()

Fermi level as a function of charge carrier concentration per cm³ and temperature

Electron Holes Donors N_D

$$N_{c} \exp \left\{ \frac{E_{F} - E_{C}}{kT} \right\} + \frac{N_{A}}{\exp \left\{ \frac{E_{A} - E_{F}}{kT} \right\} + 1} = N_{V} \exp \left\{ \frac{E_{V} - E_{F}}{kT} \right\} + \frac{N_{D}}{\exp \left\{ \frac{E_{F} - E_{D}}{kT} \right\} + 1}$$

As shown, the Fermi level is a function of the donor or acceptor levels for completely ionized defects

Defects on Compounds (Oxides) Defect Notations

- **The main symbol:** The defect species, which may be an ion, indicated by the atomic symbol for the species, or a vacant lattice site, denoted by V.
- The subscript: Indicates the lattice or interstitial site, I, occupied by the defect.
- **The superscript:** Indicates the difference in charge at the defect site relative to the charge at that site in the perfect crystal. A dot is used for an extra positive charge, and a slash denotes an extra negative charge.

Examples of Kröger-Vink defect notation

What charge where		
Cation vacancy in NaCl	V'_{Na}	
Cation interstitial in AgBr	Agi	
Anion vacancy in MgO	V	
Cation interstitial in Al ₂ O ₃	Al	
Ca2+ substituted for Na+ in NaCl	Can	
Mg ²⁺ substituted for Ti ⁴⁺ in TiO ₂	$Mg_T^{\prime\prime}$	
O ²⁻ substituted for F ⁻ in CaF ₂	O_E^{\prime}	

Important Defects:

Vacancies (cations and anions)

Interstitials

Foreign atoms

Electrons and holes

Charged defects

Various associated complexes

Conservation Rules

- Conservation of mass: Atoms are neither created nor destroyed within a system, but must be conserved
- Conservation of charge: The bulk of an ideal crystal is electrically neutral. Charged
 defects must be created in combinations that are electrically neutral. Matter can be added to
 or removed from a crystal only in electrically neutral combinations.
- Conservation of structure (lattice site ratios): The creation of lattice defects must not violate the inherent ratio of cation sites to anion sites in the structure. Thus cation and anion sites can be created or destroyed only in ratios that correspond to the stoichiometry of the compound (i.e., in electrically neutral combinations).
- Conservation of electronic states: The total number of electronic sites in a system derives directly from the electronic states of the component atoms, and must be conserved.

Law of Mass Action is Applicable
$$aA + bB = cC + dD$$

$$\frac{\left[C\right]^{c}\left[D\right]^{d}}{\left[A\right]^{a}\left[B\right]^{b}} = e^{-\frac{\Delta G^{\circ}}{bT}}$$

Replace activities with concentrations

Stoichiometry and Defect Chemistry

Intrinsic Ionic Disorder is such that the stoichiometry of the compound is maintained.
 Example: Schottky Disorder for the compound M_mX_n.

$$\frac{\left[V_{M}^{x}\right]}{\left[V_{X}^{x}\right]} = \frac{m}{n}$$

$$\left[V_M^x\right]^m \left[V_X^x\right]^n = K_s$$

These defects can be ionized

$$V_M^x = V_M^{n-} + nh^{\bullet}$$

$$V_Y^x = V_Y^{m^{\bullet}} + me'$$

$$\left[V_M^{n-}\right]^m \left[V_X^{m-}\right]^n = K_s'$$

There are nine types of intrinsic disorder.

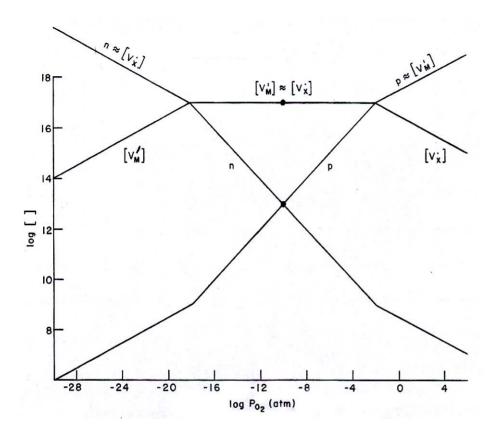
 Extrinsic Ionic Disorder usually involves the addition of a dopant, but there are also cases where such disorder can be established by reactions of the compound with the gas and stoichiometry is not maintained.

Dopant:

$$Al_2O_3 \xrightarrow{NiO} 2Al_{Ni}^{\bullet} + 3O_O^x + V_{Ni}''$$

Gas Reaction:

$$\frac{1}{2}O_2 \xrightarrow{NiO} O_O^x + V_{Ni}'' + 2h^{\bullet}$$



The Kröger-Vink diagram for MX.

Pure MX

No Dopant - Schottky Defects

Electrical Neutrality

$$n + [V_M'] = p + [V_X^{\bullet}]$$

Constant Temperature

- whether electronic or ionic conductor depends upon:

$$[V_M'][V_X^{\bullet}] = K_s$$

$$np = K_i$$

Construction of Kröger-Vink Diagram

Region I:

If
$$K_s >> K_i$$

Electrical Neutrality: $[V_M'] = [V_X^{\bullet}] = K_{s}^{\frac{1}{2}}$

1.
$$\frac{1}{2}X_2(g) = X_X^x + V_M^x$$

$$K_1 = \frac{V_M^x}{P_{X_2}^{1/2}}$$

2.
$$V_{M}^{x} = V_{M}' + h^{\bullet}$$

$$K_{2} = \frac{V_{M}' p}{V_{M}} = \frac{V_{M}' p}{K_{1}P_{X}^{1/2}}$$

$$p = \frac{K_2 K_1 P_{X_2}^{1/2}}{K_S^{1/2}}$$

3.
$$X_X^x = V_X^x + \frac{1}{2} X_{2(gas)}$$

 $K_3 = \left[V_X^x \right] P_{X_2}^{\frac{1}{2}}$

4.
$$V_X^x = V_X^{\bullet} + e'$$

$$K_4 = \frac{\left[V_X^{\bullet}\right]n}{V_X^x} = \frac{\left[V_X^{\bullet}\right]nP_{X_2}^{1/2}}{K_3}$$

$$p = \frac{K_2 K_1 P_{X_2}^{1/2}}{K_S^{1/2}} \qquad n = \frac{K_3 K_4 P_{X_2}^{-1/2}}{K_S^{1/2}}$$

Region II:

Electrical Neutrality: $p = [V_M']$

2.
$$K_{2} = \frac{\left[V'_{M}\right]p}{K_{1}P_{X_{2}}^{1/2}}$$

$$p = \left[V'_{M}\right] = \left(K_{1}K_{2}\right)^{1/2}P_{X_{2}}^{1/4}$$

$$\left[V_{X}^{\bullet}\right] = \frac{K_{S}}{\left[V'_{M}\right]} = \frac{K_{S}}{\left(K_{1}K_{2}\right)^{1/2}}P_{X_{2}}^{-1/4}$$

$$n = \frac{K_{i}}{p} = \frac{K_{i}}{\left(K_{1}K_{2}\right)^{1/2}}P_{X_{2}}^{-1/4}$$

Region III:

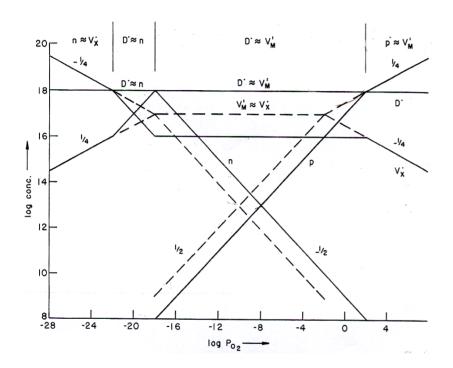
Electrical Neutrality: $n = [V_X^{\bullet}]$

4.
$$K_{4} = \frac{[V_{X}^{\bullet}]n}{K_{3}} P_{X_{2}}^{1/2}$$

$$n = [V_{X}^{\bullet}] = (K_{4}K_{3})^{1/2} P_{X_{2}}^{-1/4}$$

$$[V_{M}'] = \frac{K_{S}}{[V_{X}^{\bullet}]} = \frac{K_{S}}{(K_{4}K_{3})^{1/2}} P_{X_{2}}^{1/4}$$

$$p = \frac{K_{i}}{n} = \frac{K_{i}}{(K_{4}K_{3})^{1/2}} P_{X_{2}}^{1/4}$$



The Kröger-Vink diagram for donor-doped MX with the parameters given in the text: dashed lines, diagram for pure MX.

Constant Temperature

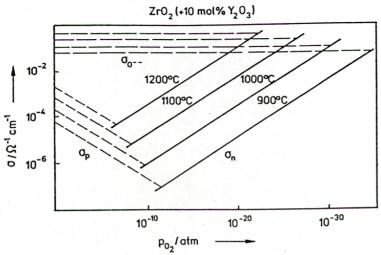
D is a dopant

Electrical Neutrality

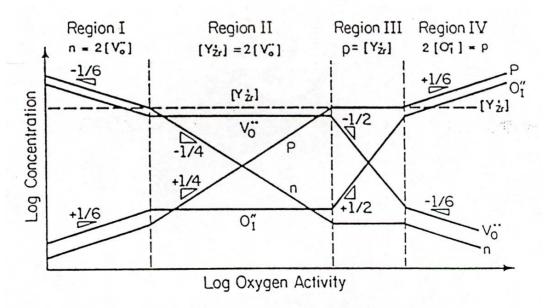
$$n + [V_M'] = p + [V_X^{\bullet}] + [D_M^{\bullet}]$$

where;

$$DX_2 \xrightarrow{MX} D_M^{\bullet} + V_M' + 2X_X$$



Partial conductivities of electrons, electron defects and oxygen ions in ZrO₂ (+ 10 mol-% Y₂O₃) at different temperatures as a function of the oxygen partial pressure



The defect concentration dependence on oxygen activity in YSZ.

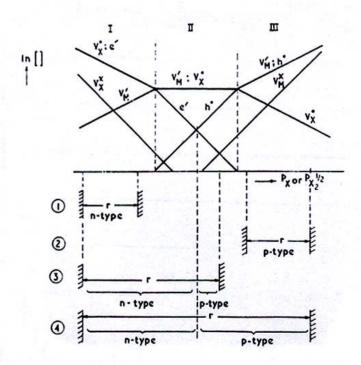
Compositional Gradients

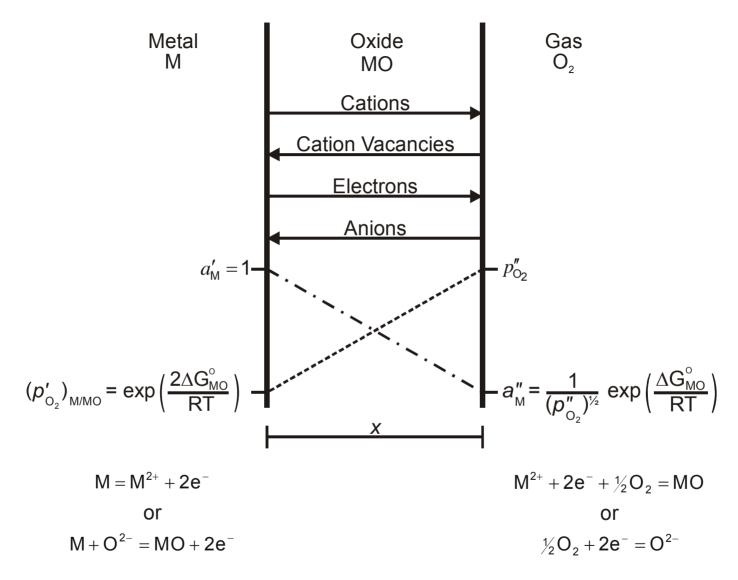
• The diagram shows various possibilities for the dependence of basic imperfections on the partial pressure as found in simple ionic conductors. Other diagrams of course are possible depending upon the magnituted of constants such as K_i and K_s as well as the particle defect types. AS this diagram indicates situations (1) and (2) are relatively simple but (3) and (4) show cases in which two or three ranges are present in a growing layer. When only one type of imperfection is mobile, the particle current is constant throughout the layer providing the deviations from stoichiometry are small for the compound. When two different atomic imperfections are involved the fluxes of these imperfections need no longer be constant through the layer. For such cases considering V_M and V_X as the diffusing species, when:

$$\frac{dJ_{V_{M'}}}{dx} \neq 0 \qquad \frac{dJ_{V_X^{\bullet}}}{dx} \neq 0$$

then we must have:

$$\frac{dJ_{V_M'}}{dx} = \frac{dJ_{V_X^{\bullet}}}{dx}$$





Overall reaction: $2M + O_2 = 2MO; \Delta G_{MO}^{\circ}$

Flux of Species due to Gradient in the **Electrochemical Potential**

$$j_{i} = -L_{i} \left(\frac{\partial \mu_{i}}{\partial X} + Z_{i} F \frac{\partial \phi}{\partial X} \right)$$

J_i: moles/cm²sec Z_i: charge on species I

X: oxide thickness

F: Faraday's constant

μ_i: chemical potential

φ: electrical potential

L_i: Parameter containing Di (diffusion coefficient) or κ_i (conductivity)

Cation:
$$J_1 \left(\frac{eq}{cm^2 - s} \right) = Z_1 j_1 = -\frac{\kappa_1}{Z_1 F^2} \left(\frac{\partial \mu_1}{\partial X} + Z_1 F \frac{\partial \phi}{\partial X} \right)$$

Anion:
$$J_2 = |Z_2| j_2 = -\frac{\kappa_2}{|Z_2|F^2} \left(\frac{\partial \mu_2}{\partial X} - |Z_2|F \frac{\partial \phi}{\partial X} \right)$$

Electrons:
$$J_3 = j_3 = -\frac{\kappa_3}{F^2} \left(\frac{\partial \mu_3}{\partial X} - F \frac{\partial \phi}{\partial X} \right) = -\frac{\kappa_3}{F^2} \frac{\partial \eta_3}{\partial X}$$

For the oxide to stay locally electrically neutral,

$$J_1 + |J_2| = J_3$$

The parabolic rate constant defined as:

$$\Delta x^2 = 2kt$$

For an electronic conductor

For an ionic conductor

$$k = \int_{a_0'}^{a_0''} \left(\frac{Z_1}{|Z_2|} D_1 + D_2\right) d \ln a_0$$

$$or$$

$$k = -\frac{\widetilde{V}}{F^2} \int_{-K_1}^{\mu_M''} \frac{\kappa_1 + \kappa_2}{Z_1} d\mu_M$$

$$k = \frac{RT\widetilde{V}}{F^2} \int_{a_0'}^{a_0'} \left(\frac{\kappa_3}{|Z_2|} \right) d \ln a_0$$

$$a_O \equiv P_{O_2}^{1/2}(atm)$$

$$\widetilde{V} = \text{equivalent volume}$$

The Parabolic Rate Constant in Terms of Defect Concentrations

 Z_1 and Z_2 can be related to the oxide composition for electrical neutrality $|Z_2|M^{Z_1}=Z_1O^{|Z_2|}$. Hence,

$$M_{|Z2|}O_{Z1}$$
 , or $MO_{(Z1/Z2)}$

for incorporation of O_2 into $MO_{(Z1/Z2)}$

$$\frac{Z_1}{2}O_2 \to Z_1O_0^x + |Z_2|V_M^{Z_1^-} + Z_1|Z_2|h^{\bullet}$$

Upon applying the law of mass action to the above expression and satisfying the electrical neutrality condition

$$d \ln a_O = \frac{|Z_2|(1+Z_1)}{Z_1} d \ln \left[V_M^{Z_1^-} \right]$$

Substituting into the previous expression for k where D1>>D2

$$k = \int_{\left[V_{M}^{Z_{1}^{-}}\right]^{\prime}}^{\left[V_{M}^{Z_{1}^{-}}\right]^{\prime}} \left[1 + Z_{1}\right] D_{1} d \ln \left[V_{M}^{Z_{1}^{-}}\right]$$

For cation diffusing via a vacancy mechanism

$$D_{1} = \begin{bmatrix} V_{M}^{Z_{1}^{-}} \end{bmatrix} D_{V_{M}^{Z_{1}^{-}}}$$

$$k = (1 + Z_{1}) \int_{\begin{bmatrix} V_{M}^{Z_{1}^{-}} \end{bmatrix}'} D_{V_{M}^{Z_{1}^{-}}} dV_{M}^{Z_{1}^{-}}$$

Assuming $D_{V_{M}^{Z_{\bar{1}}}}$ is constant

$$k = (1 + Z_1) D_{V_M^{Z_1^-}} \left[\left[V_M^{Z_1^-} \right]' - \left[V_M^{Z_1^-} \right] \right]$$

For p-type oxides $\left[V_{\scriptscriptstyle M}^{\scriptscriptstyle Z_{\scriptscriptstyle 1}^{\scriptscriptstyle -}}\right]'>>\left[V_{\scriptscriptstyle M}^{\scriptscriptstyle Z_{\scriptscriptstyle 1}^{\scriptscriptstyle -}}\right]'$

$$k = (1 + Z_1)D_{V_M^{Z_1^-}} \left[V_M^{Z_1^-} \right]'$$
$$k = (1 + Z_1)D_1''$$

Where D_1 " is the value of D_1 at the $MX_{\frac{Z_1}{|Z_1|}}$ -gas interface

In case of n-type compound

 $k = (1 + Z_1)D_1'$ where D_1 ' is the value of D_1 at the $M - MX_{\frac{Z_1}{|Z_2|}}$ interface.

Electrical Conduction

$$\sigma_n = pe\mu_n$$

$$\sigma_e = ne\mu_e$$

 σ_n , σ_e electrical conductivity via holes or electrons

p, n concentration of holes or electrons

 μ_h , μ_e mobility of holes or electrons

Consider Cr₂O₃ added to NiO with Schottky Defects

$$Cr_2O_2 \xrightarrow{NiO} 2Cr_{Ni}^{\bullet} + 3O_O^x + V_{Ni}''$$

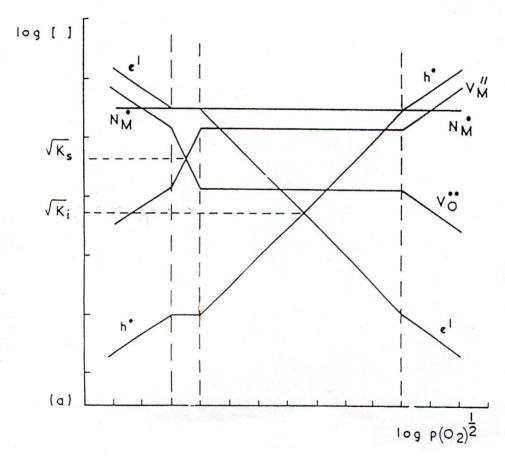
$$V_M^x \to V_M'' + 2h^{\bullet}$$

$$\frac{1}{2}O_2 \to V_M^x + O_O^x$$

Applying law of mass action

$$K = const. = \frac{[V_M'']p^2}{P_{O_2}^{1/2}}$$

Kröger-Vink Diagram Applicable to Cr₂O₃ Addition to NiO with Schottky Defects



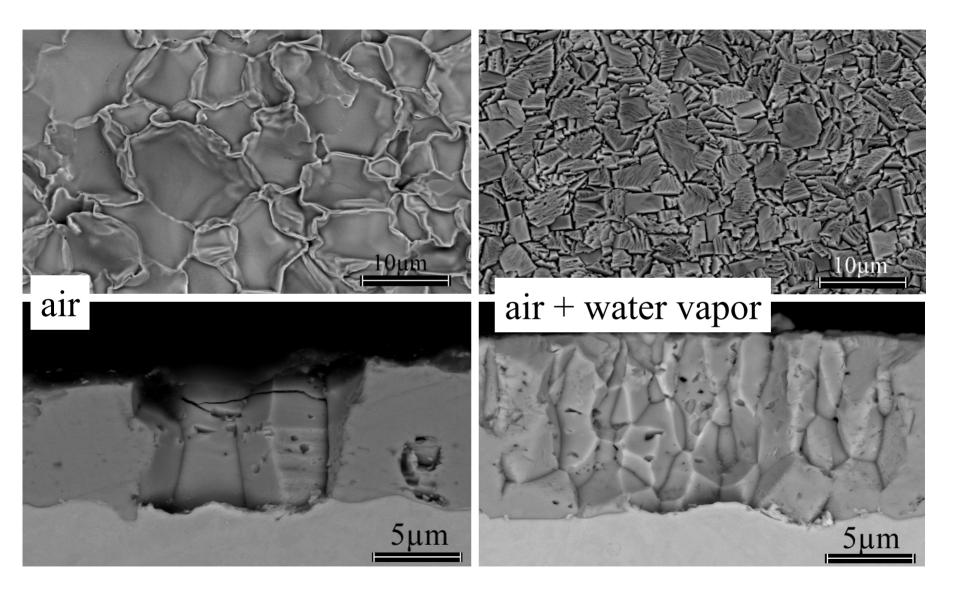
- 1. For $[Cr^{\circ}_{N_i}]=2[V^{"}_{N_i}]$ and constant $P(O_2)$ as increase Cr_2O_3 in solution in NiO, $[Cr^{\circ}_{N_i}]$ and $[V^{"}_{N_i}]$ increase, p decreases.
- 2. If dope with a fixed amount of Cr_2O_3 and $[Cr_{Ni}]=2[V_{Ni}]$, p increases as $P(O_2)$ increases.
- 3. If $p=2[V''_{Ni}]$ the concentration of Cr_2O_3 is too low to affect $[V''_{Ni}]$ and p and they increase with $P(O_2)$.

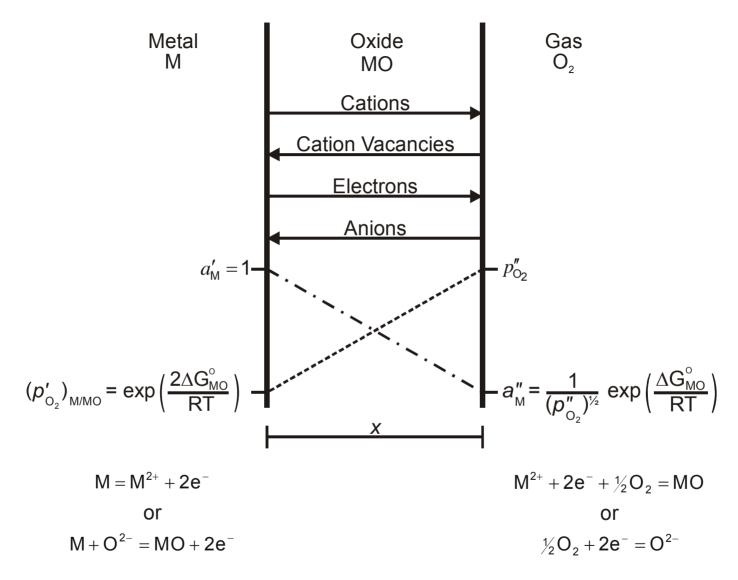
Growth of Oxides on Pure Metals

Focus on Diffusion-Controlled Growth

- Simple Parabolic Oxidation Model
- 2. Effect of Oxygen Partial Pressure
- 3. Bulk vs. Grain Boundary Diffusion

Pure Ni exposed for 1 hour @ 1100°C





Overall reaction: $2M + O_2 = 2MO; \Delta G_{MO}^{\circ}$

Simplified Treatment of Diffusion-Controlled Oxidation

$$j_{M^{2+}} = -j_{V_M} = D_{V_M} \frac{C_{V_M}'' - C_{V_M}'}{x}$$

$$j_{M^{2+}} = \frac{1}{V_{ox}} \frac{dx}{dt} = D_{V_M} \frac{C_{V_M}'' - C_{V_M}'}{x}$$

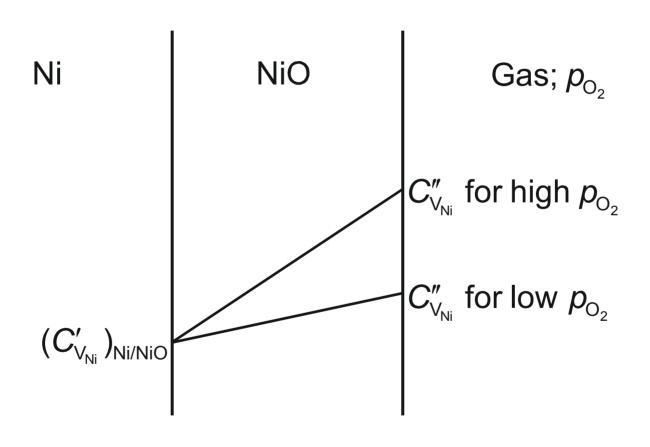
$$\frac{dx}{dt} = \frac{k'}{x}$$

$$k' = D_{V_M} V_{ox} (C_{V_M}'' - C_{V_M}')$$

$$x^2 = 2k't$$

Effect of oxygen partial pressure

(p-type oxide)



Effect of oxygen partial pressure

$$\frac{1}{2}O_{2} = O_{0} + h' + V_{Co}'$$

$$C_{h'}C_{V_{Co}''} = Kp_{O_{2}}^{1/2}$$

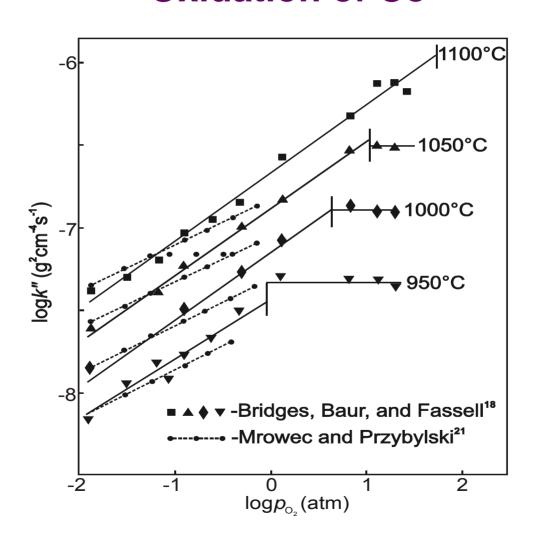
$$C_{h'} = C_{V'_{Co}}$$

$$C_{V_{M}} = const.p_{O_{2}}^{1/4}$$

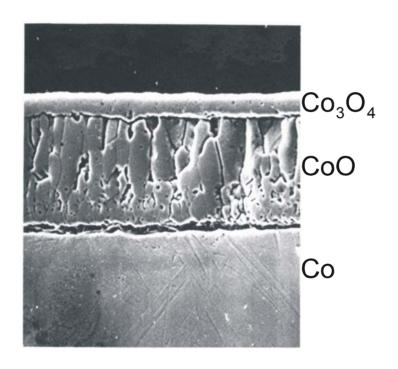
$$C_{V_{M}} = const.p_{O_{2}}^{1/n}$$

$$k' \propto \left[\left(p_{O_{2}}'' \right)^{1/n} - \left(p_{O_{2}}' \right)^{1/n} \right]$$

Effect of oxygen partial pressure Oxidation of Co

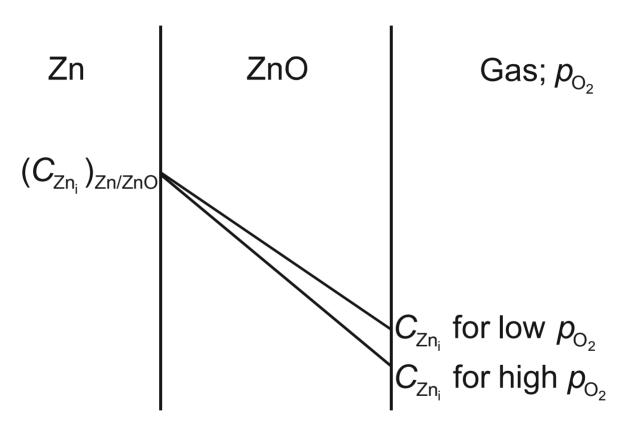


Cross-section of Co oxidized in Air at 750°C



Effect of oxygen partial pressure

(n-type oxide)



Effect of oxygen partial pressure

$$j_{M^{2+}} = \frac{1}{V_{ox}} \frac{dx}{dt} = D_{M_i} \frac{C'_{M_i} - C''_{M_i}}{x}$$

$$k' = D_{M_i} V_{ox} (C'_{M_i} - C''_{M_i})$$

$$ZnO = Zn_i^{-} + 2e' + \frac{1}{2} O_2$$

$$K'_1 = C_{Zn_i^{-}} C_{e'}^2 p_{O_2}^{1/2}$$

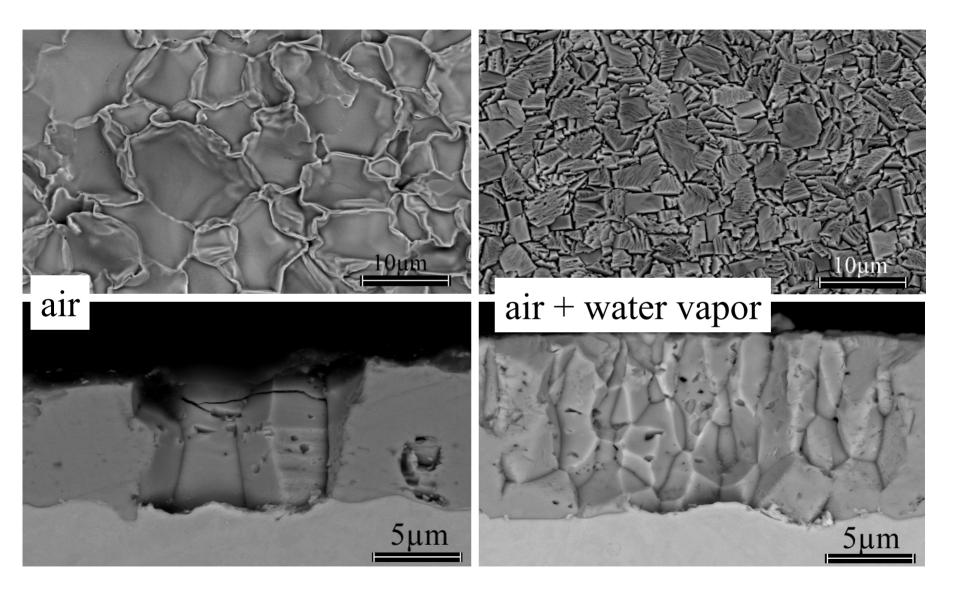
$$2C_{Zn_i^{-}} = C_{e'}$$

$$K'_1 = 4C_{Zn_i^{-}}^3 p_{O_2}^{1/2}$$

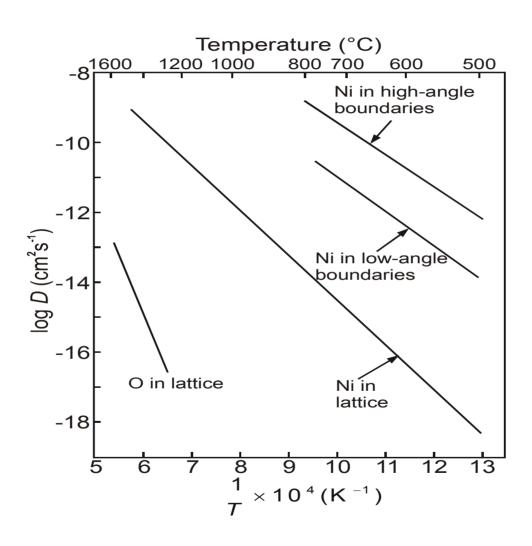
$$C_{Zn_i^{-}} = \left(K'_1 / 4\right)^{1/3} p_{O_2}^{-1/6} = const. p_{O_2}^{-1/6}$$

$$k'_{ZnO} = const. \left[\left(\frac{1}{p_{O_2}}\right)^{1/6} - \left(\frac{1}{p_{O_2}}\right)^{1/6} \right]$$

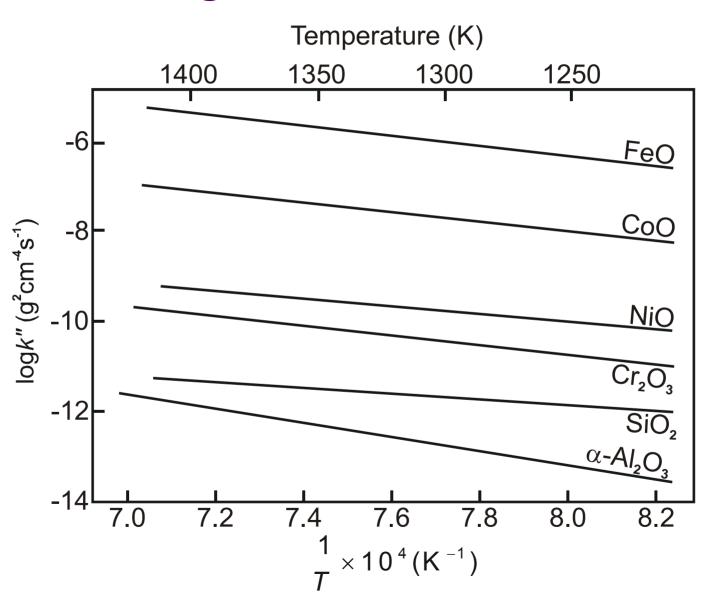
Pure Ni exposed for 1 hour @ 1100°C



Transport Paths - NiO



Relative growth rates of several oxides



Selective Oxidation

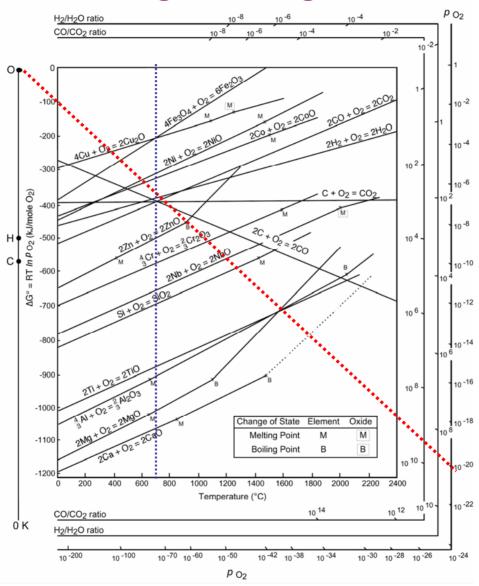
The approach to developing high temperature corrosion resistance in alloys is to have the reactants, namely the alloy and the gas, form a reaction product that separates the reactants and that allows slow transport of the reactants through it.



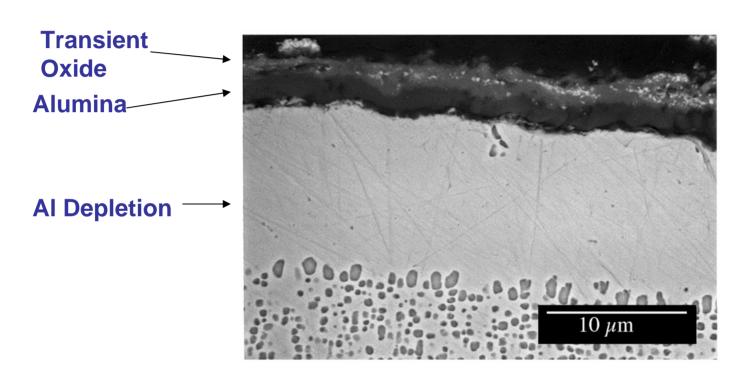
Most environments encountered in practice contain some oxygen, hence protective barriers are usually α -Al₂O₃, Cr₂O₃ and SiO₂.

For SOFC-ICs one wants to avoid the selective oxidation of Si and Al.

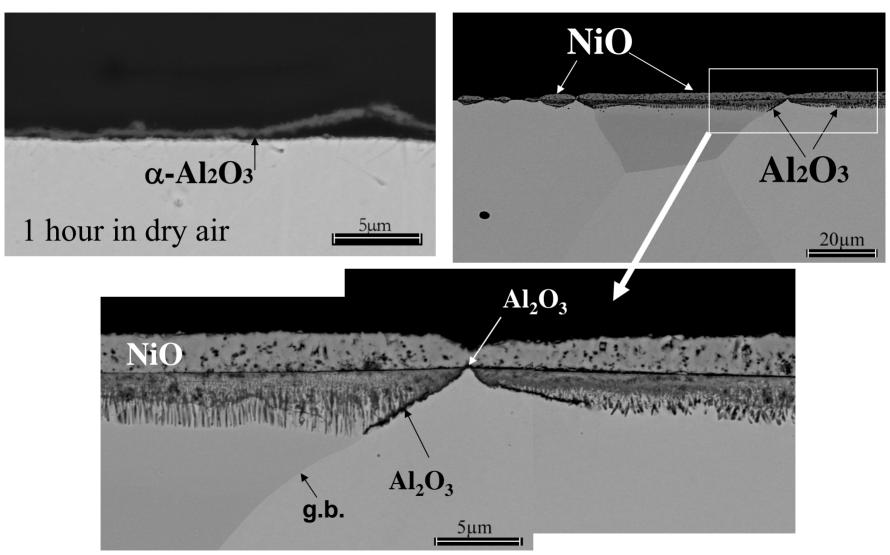
Ellingham Diagram



PWA 1484 oxidized at 1100°C

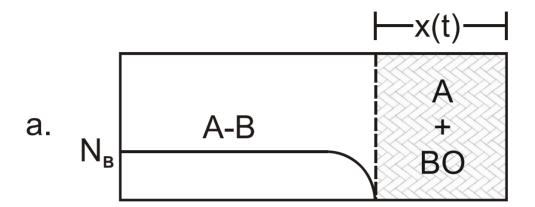


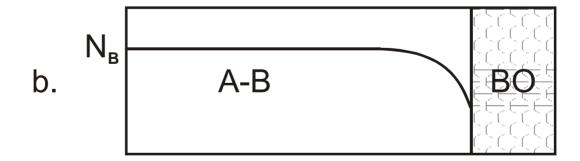
Cross-sections of Ni-8Cr-6Al oxidized @ 1100°C



1 min in air with water vapor (0.1atm)

Transition to External Scale Formation





Transition to External Scale Formation

Equating the molar fluxes of solute B and oxygen

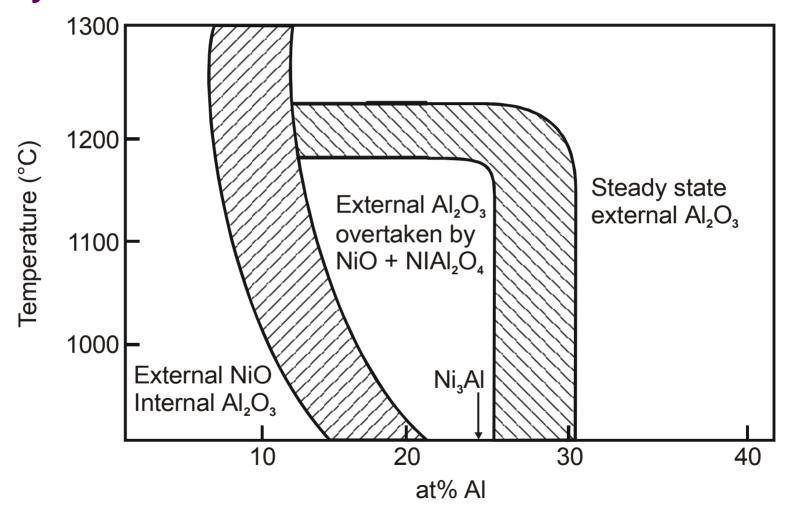
$$N_B^{(o)} > \left[\frac{\pi g^*}{2\nu} N_O^{(S)} \frac{D_O V_m}{D_B V_{ox}} \right]^{1/2}$$

Maintaining the Growth of an External Scale

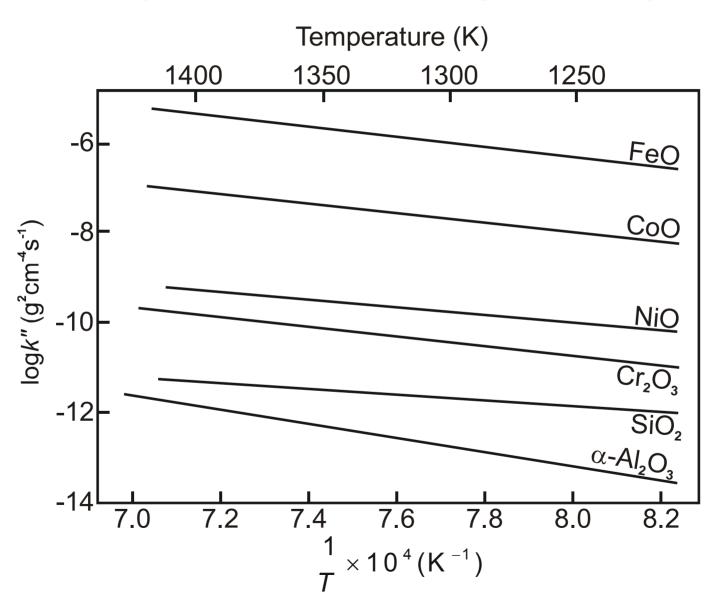
Equating the molar flux of solute B to that being required for oxide growth

$$N_B^{(o)} = \frac{V_m}{32\nu} \left(\frac{\pi k_p}{D_B}\right)^{1/2}$$

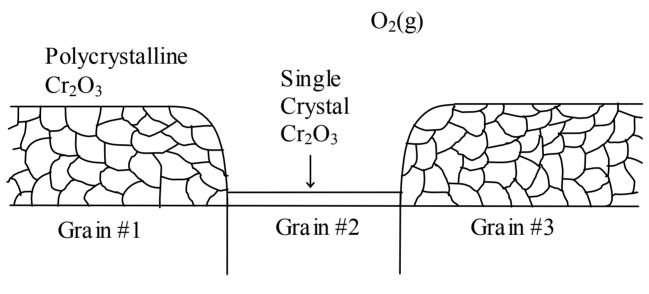
Effect of Temperature and Al Content on the Formation and Continued Growth of External Alumina on Ni-Al Alloys



Relative Growth Rates of Several Oxides



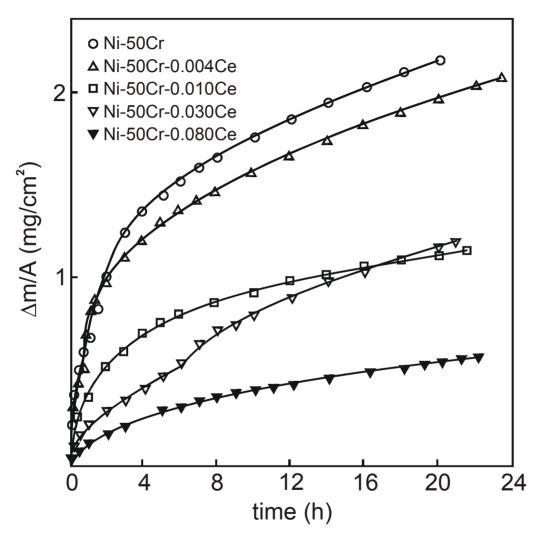
Oxidation of Chromia-forming Alloys



Polycrystalline Cr

Caplan and Sproule, Oxid. Of Metals, 1975

Isothermal Oxidation – RE Effect



Ecer, and Meier, Oxid. Of Metals, 1979 Singh, Ecer, and Meier, Oxid. Of Metals, 1982

Oxidation of Ferritic Stainless Steels

Alloy	Fe	Cr	C	Mn	Si	Ni	Mo	Ti	Al	Zr	P	S	La+Ce
Crofer	bal.	22.0	0.005	0.50				0.08			0.016	0.002	0.06 La
E-brite	bal.	26.0	0.001	0.01	0.025		1.0				0.020	0.020	
26Cr Ferritic	bal.	26.0		~ 1.0	~ 1.0		1.0						
AL453	bal.	22.0	0.030	0.30	0.300			0.02	0.60		0.020	0.030	0.10
ZMG232	bal.	22.0	0.020	0.50	0.400	0.26			0.21	0.22			0.04 La

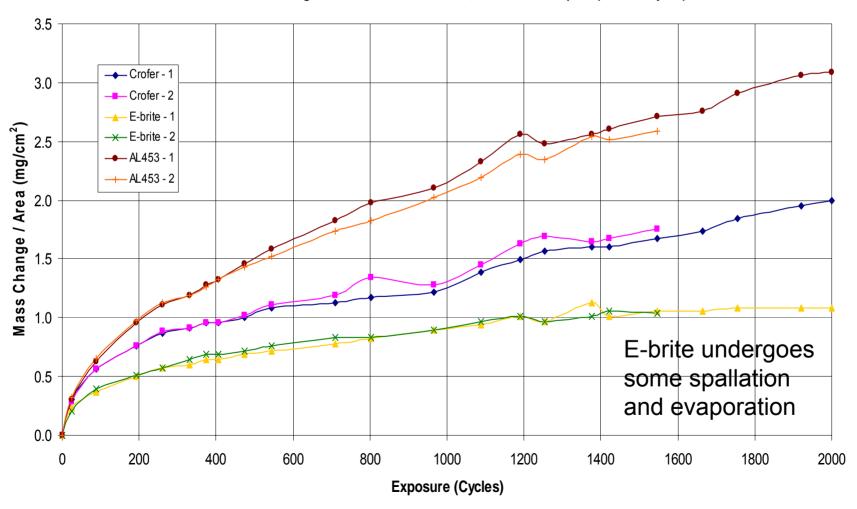
Exposure Conditions

T = 700°C, 800°C, 900°C One-Hour Cycles

Atmosphere: Dry Air (SCG)

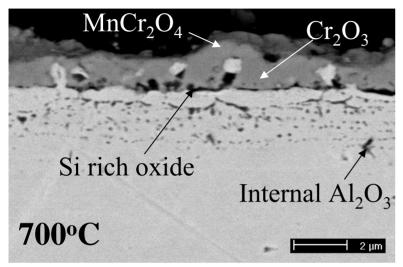
Dry Air Exposures – 900°C

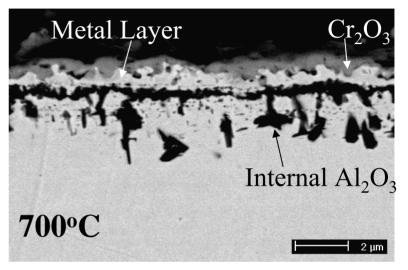
Time vs. Mass Change / Area for Crofer, E-brite, and AL453 Samples (900°C, Dry Air)

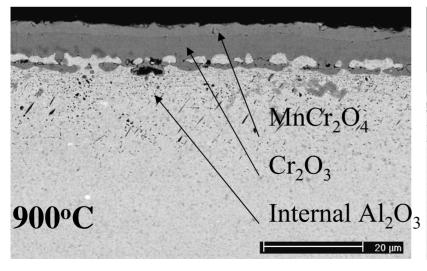


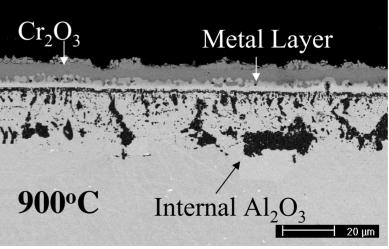
Internal Oxidation of Impurities

Crofer AL453



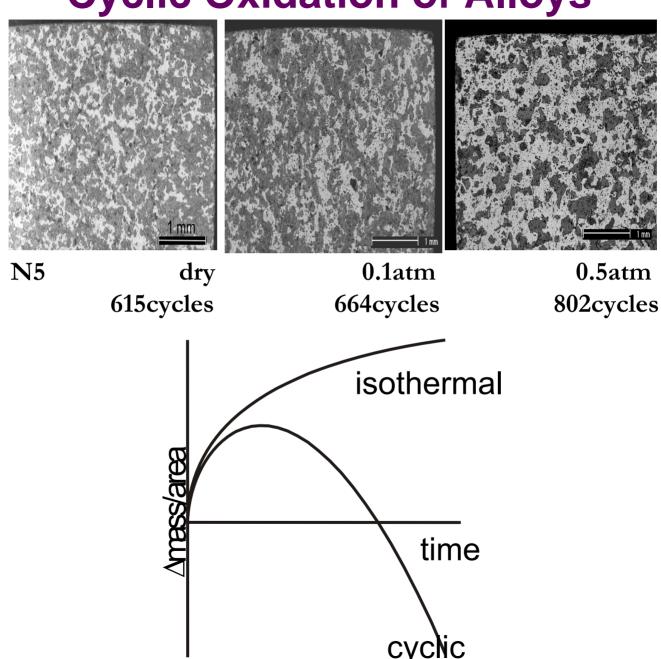




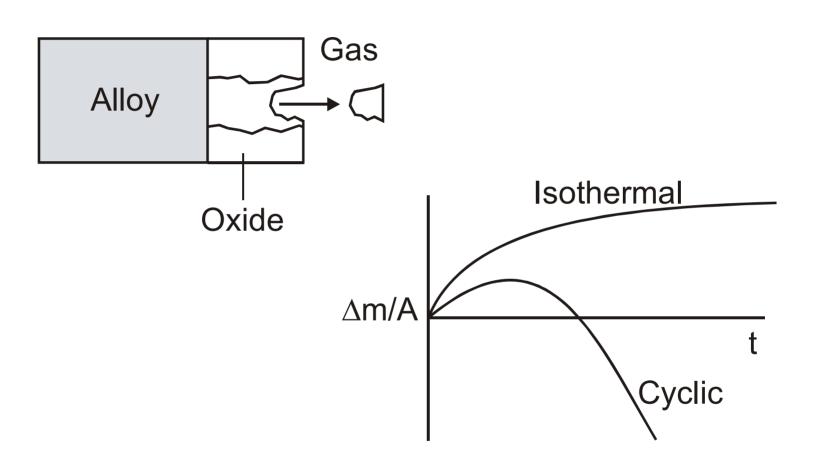


Cyclic Oxidation of Alloys

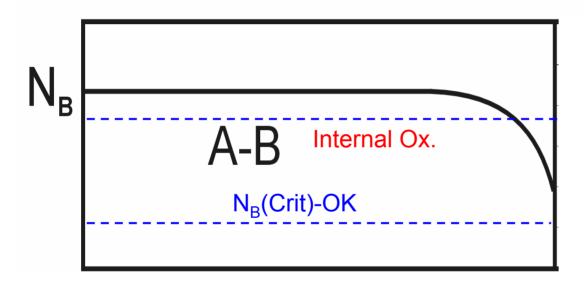




Cyclic Oxidation



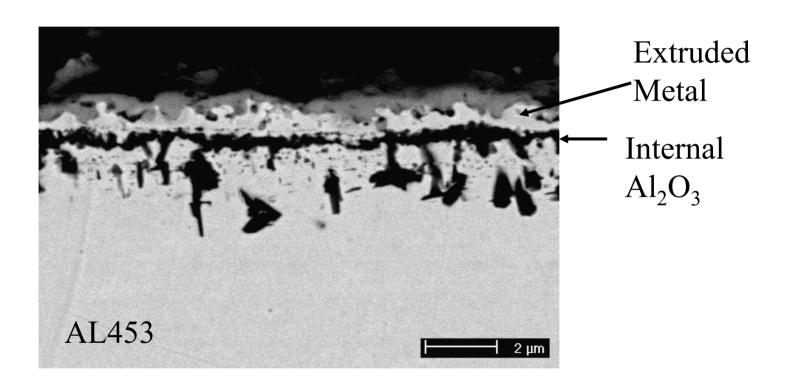
Effects of Alloy Depletion and Scale Spallation



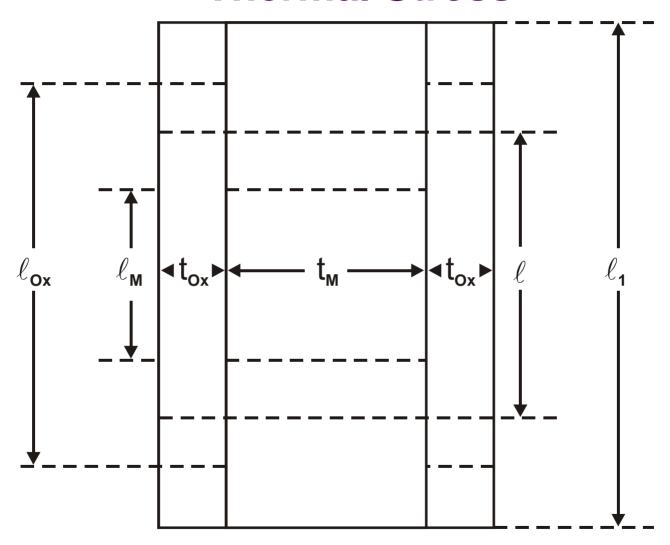
Origins of Oxide Stress

- Growth Stresses stresses arising from the nature of the oxide growth process
- Thermal Stresses stresses arising form the thermal expansion mismatch between metal and oxide.
- Applied Loads

Stress Generation by Internal Oxidation



Thermal Stress



Origin of Thermal Stress

$$\varepsilon_{thermal}^{metal} = \alpha_M \Delta T$$

$$\varepsilon_{thermal}^{Ox} = \alpha_{Ox} \Delta T \qquad \Delta T = T_{L} - T_{H}$$

$$\Delta T = T_L - T_H$$

$$\varepsilon_{mech}^{metal} = \frac{\sigma_M (1 - v_M)}{E_M}$$

$$\varepsilon_{mech}^{Ox} = \frac{\sigma_{Ox}(1 - v_{Ox})}{E_{Ox}}$$

$$\varepsilon_{thermal}^{metal} + \varepsilon_{mechanical}^{metal} = \varepsilon_{thermal}^{Ox} + \varepsilon_{mechanical}^{Ox}$$

$$\sigma_M t_M + 2\sigma_{Ox} t_{Ox} = 0$$
 Force Balance

$$\alpha_M \Delta T = \frac{2\sigma_{Ox}t_{Ox}(1-v_M)}{t_M E_M} = \alpha_{Ox}\Delta T + \frac{\sigma_{Ox}(1-v_{Ox})}{E_{Ox}}$$

$$\sigma_{Ox} = \frac{-(\alpha_{Ox} - \alpha_M)\Delta T}{\frac{2t_{Ox}(I - \nu_M)}{t_M E_M} + \frac{(I - \nu_{Ox})}{E_{Ox}}}$$

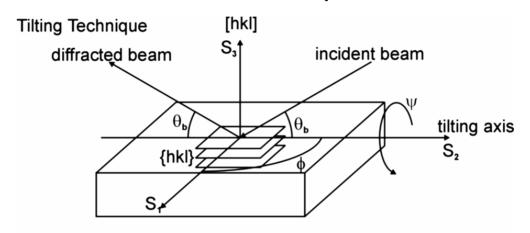
$$\sigma_{Ox} = \frac{-E_{Ox}(\alpha_{Ox} - \alpha_{M})\Delta T}{(1 - \nu)\left(1 + 2\frac{t_{Ox}E_{Ox}}{t_{M}E_{M}}\right)}$$
 If $\nu_{M} \approx \nu_{Ox}$

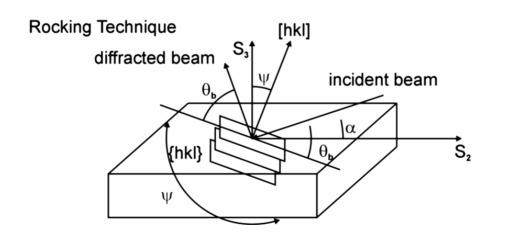
Thermal Stress if $t_{Ox} \ll t_{M}$

$$\sigma_{Ox} = \frac{-E_{Ox}(\alpha_{Ox} - \alpha_{M})\Delta T}{(1-\nu)}$$

Stress Measurement

XRD Techniques





Stress Measurement

 d-spacing as a function of the biaxial stress and the tilt angle

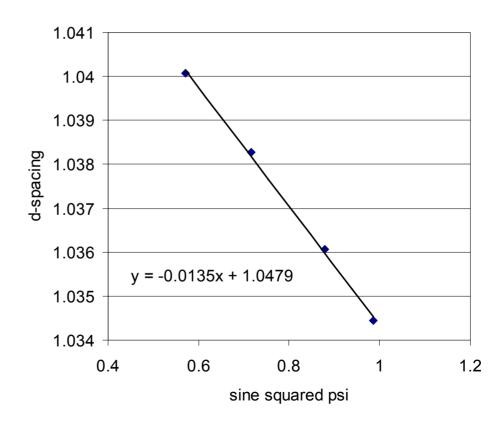
$$d_{\psi} = \frac{1}{2} s_2 \cdot \sigma_o \cdot d_o \cdot \sin^2 \psi + d_o (2s_1 \cdot \sigma_o + 1)$$

Calculation of Stress

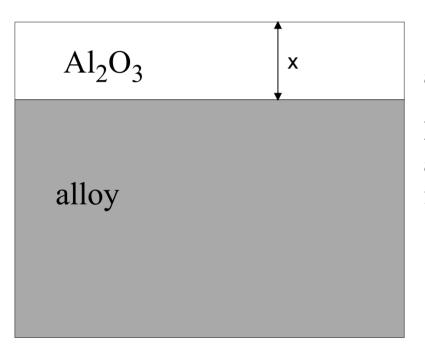
slope =
$$\frac{1}{2} s_2 \cdot \sigma_o \cdot d_o$$

• -4.14 +/- 0.21GPa

226 FIT, (NI,Pt) aluminide, ridges removed, 40h @ 1100°C



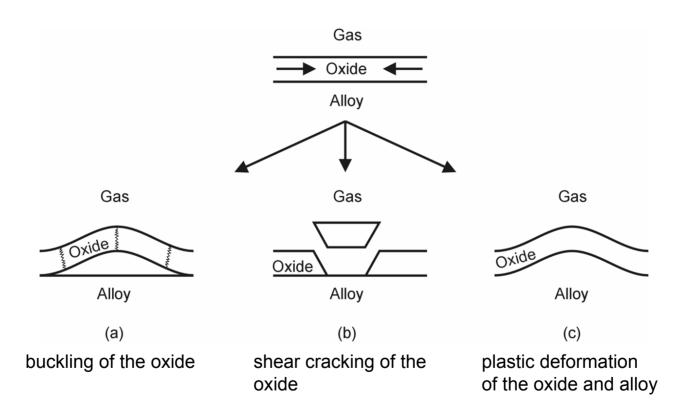
Oxide Failure

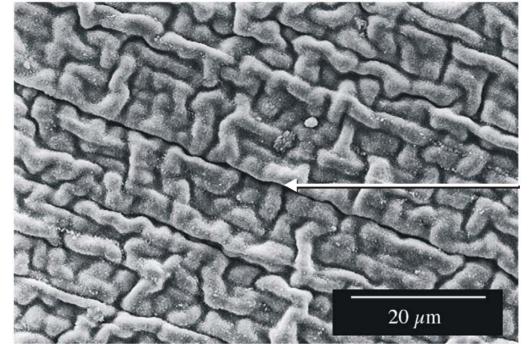


Stored elastic energy of alumina $\approx f(s_{OX}, x_{OX})$

Fracture resistance of the alumina/alloy interface ≈ f(morphology, composition)

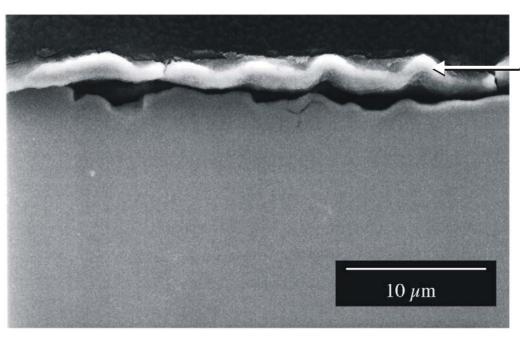
Response to Stresses





Example of Buckling

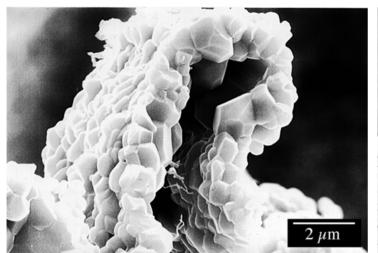
Polishing mark

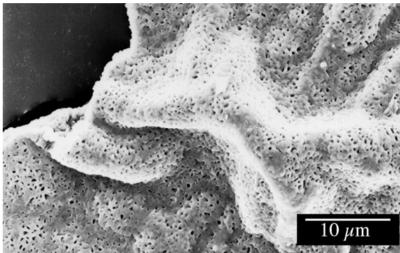


Alumina scale

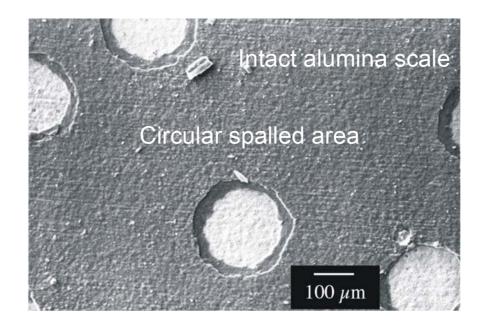
Spallation of Alumina Scale by Buckling

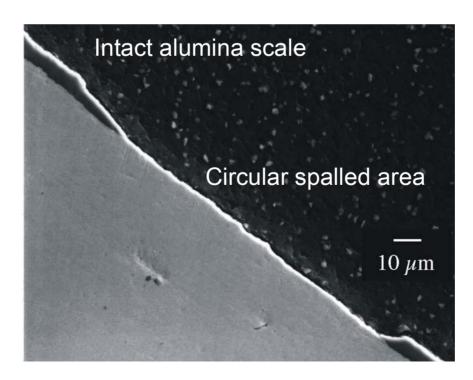
FeCrAl (TMP) oxidized at 1100°C for 120 hours.



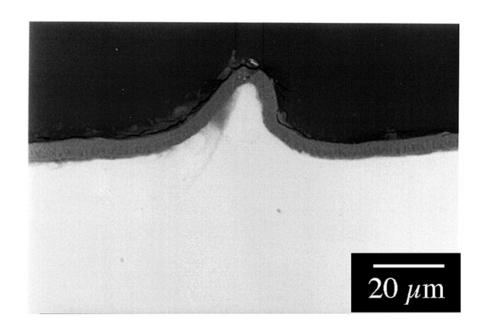


Circular Buckles

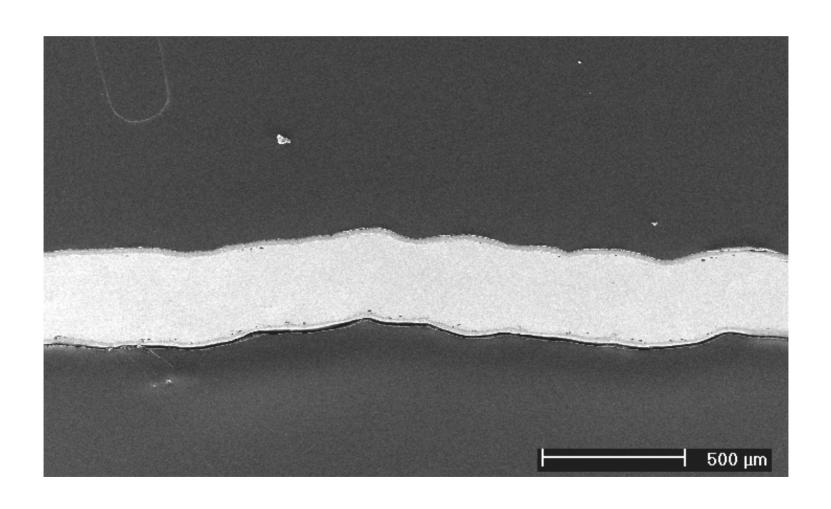




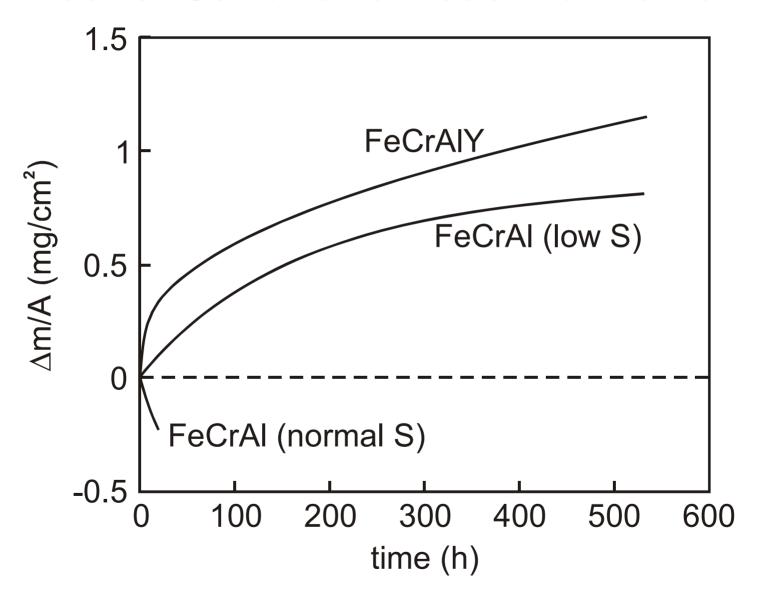
FeCrAlTi Cyclically Oxidized for 288h at 1100°C



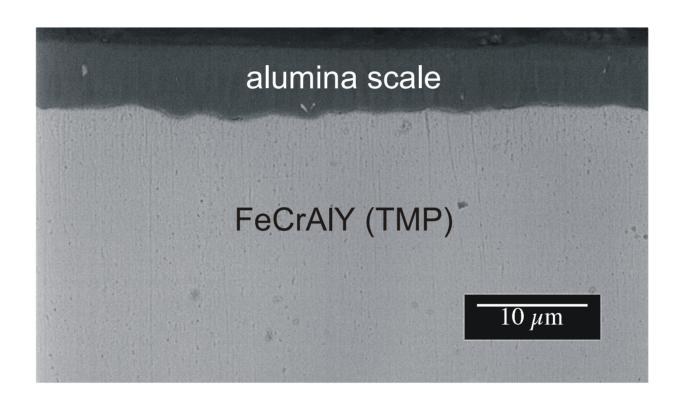
Deformation of Crofer During Cyclic Oxidation



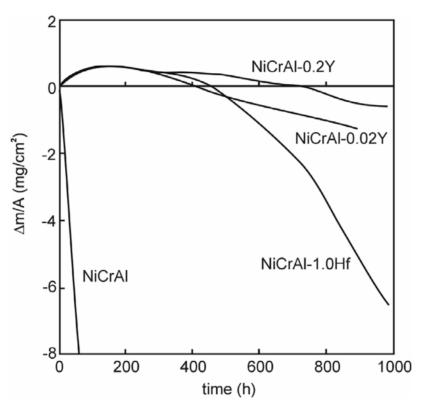
Effect of Sulfur and Reactive Element



Effect of Yttrium

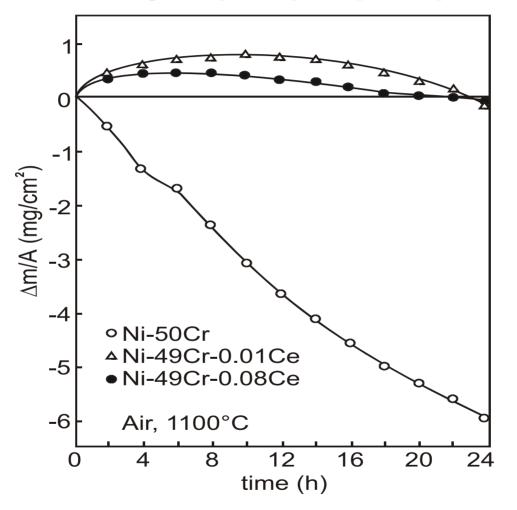


Long Term Cyclic Oxidation Testing



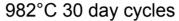
Cyclic oxidation kinetics for several Ni-Cr-Al alloys exposed at 1100°C.

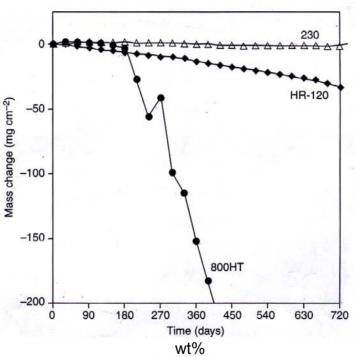
Reactive Element Effect for a Chromia Former



Cyclic Oxidation

Alloys initially are Cr₂O₃-formers

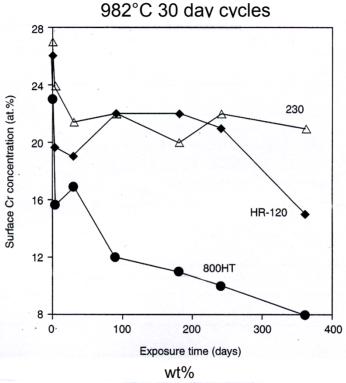




					,			
Alloy	Cr	Ni	Fe	Co	Mo	W	С	Others
800HT	21	32.5	Bal.	_			0.08	0.8Mn, 0.5Si, 0.4Cu, 0.4Al, 0.4Ti
HR-120	25	37	Bal.	3*	2.5*	2.5*	0.05	0.7Mn, 0.7Nb, 0.6Si, 0.2N, 0.1Al, 0.005B
230	22	Bal.	3*		2	14	0.1	0.5Mn, 0.4Si, 0.3Al, 0.02La, 0.015B*

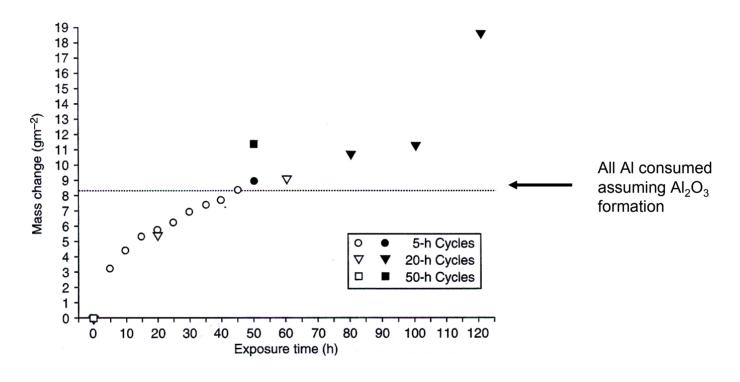
More adherent oxide

Chromium depletion due to spalling of oxide



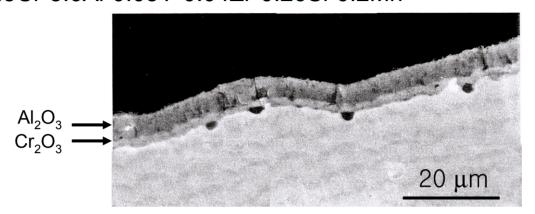
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Alloy initially is an Al₂O₃-Former

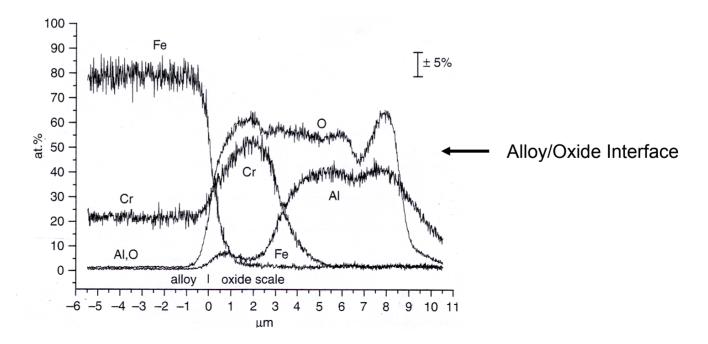


(wt%) Fe-20.5Cr-5.2Al-0.002Zr-0.39Si-0.01Ti-0.25Mn 1200°C Filled Symbols First Evidence of Color Change

Fe-20.3Cr-5.6Al-0.05Y-0.04Zr-0.26Si-0.2Mn



1200°C, 160 hr 20 hr cycles air



Oxidation of Al and Cr In a Fe-25Cr-5Al(wt%) Alloy

At 1200°C to oxidize aluminum:

$$2Al(alloy) + \frac{3}{2}O_{2} = Al_{2}O_{3}$$

$$\Delta G_{Al_{2}O_{3}}^{\circ} = -288,091 \frac{cal}{mole}$$

$$K = e^{-\frac{\Delta G_{Al_{2}O_{3}}^{\circ}}{RT}} = \frac{1}{a_{Al}^{2}P_{O_{2}}^{\frac{3}{2}}}$$

$$\frac{Gas}{Alloy} \qquad P_{O_{2}} = \frac{2.43x10^{-29}}{a_{Al}^{\frac{4}{3}}}$$

Oxidation of Al and Cr In a Fe-25Cr-5Al(wt%) Alloy

Similarly the oxygen pressure to oxidize chromium in the alloy is

$$2Cr(Alloy) + \frac{3}{2}O_2 = Cr_2O_3$$

$$\Delta G_{Cr_2O_3}^{\circ} = -180,740 \frac{cal}{mole}$$

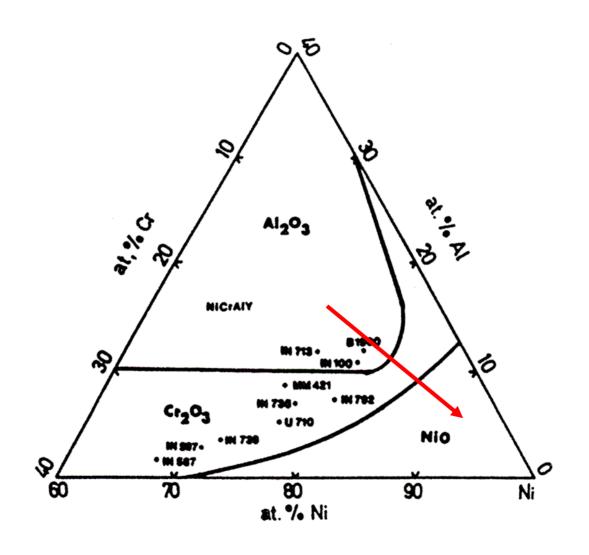
$$P_{O_2} = \frac{1.12x10^{-18}}{a_{Cr}^{4/3}}$$
if $a_{AI} \sim 10^{-2}$ $\left(P_{O_2}\right)_{Al_2O_3/Alloy} = 1.1x10^{-26} atm$

$$a_{Cr} \sim 0.25$$
 $\left(P_{O_2}\right)_{oxidizeCri\ nAlloy} = 7.1x10^{-18} atm$

Chromium will not be oxidized until $PO_2 = 1.8 \times 10^{-17}$ hence a_{AI} must be reduced to:

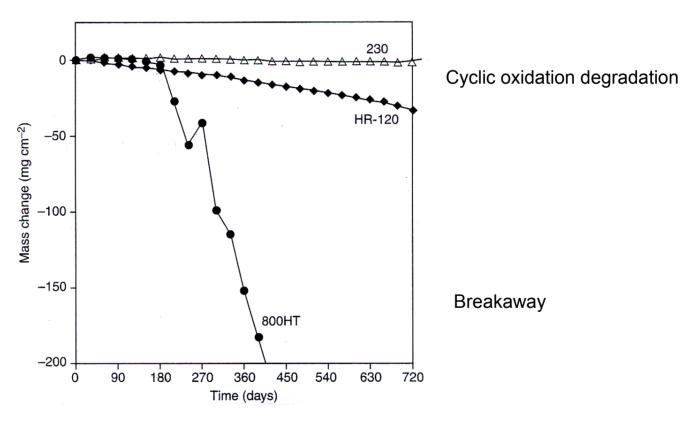
$$a_{AI} = 2.5 \times 10^{-9} atm$$

Ni-Cr-Al Cyclic Oxidation Degradation



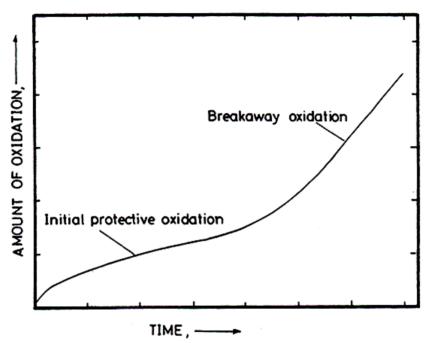
Cyclic Oxidation Degradation versus Breakaway

 The difference between cyclic oxidation degradation and breakaway is somewhat subtle:



Cyclic Oxidation at 982°C

Breakaway Can Also Occur Under Isothermal Conditions

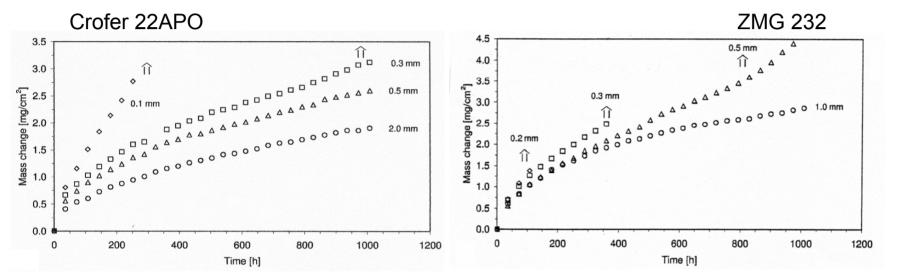


Schematic illustration of the kinetics of breakaway oxidation.

- When breakaway is observed under isothermal conditions, the alloy usually is not very oxidation resistant (e.g. Zr, Nb)
- If the alloy is oxidation resistant extremely long isothermal oxidation exposures are required at high temperatures.

Lifetime Prediction to Breakaway

900°C Lifetime Prediction

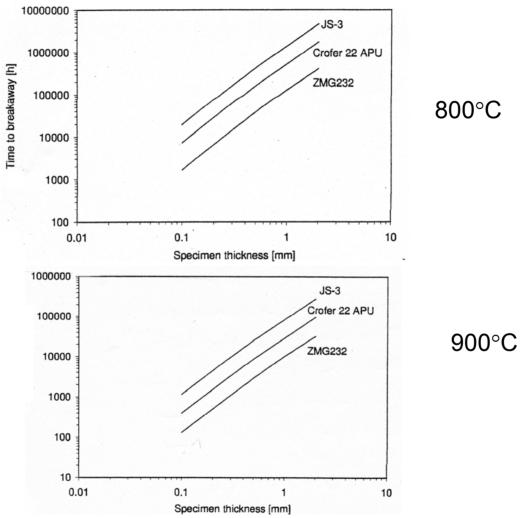


Cyclic Oxidation (2 hr hot, 15 min cool)

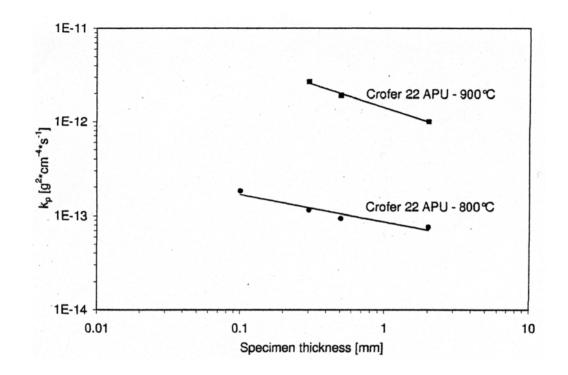
Composition (wt%)

Steel	Fe	Cr	Mn	Ti	La	Si	Al	Ni	Zr	С	N	S
Crofer 22APU	Bal.	22.6	0.4	0.06	0.07	0.11	0.12	0.16	-	0.005	0.01	<0.001
ZMG232	Bal.	22.1	0.48	-	<0.01	0.36	0.19	0.31	0.13	0.0017	0.0047	<0.001

Calculated Lifetime

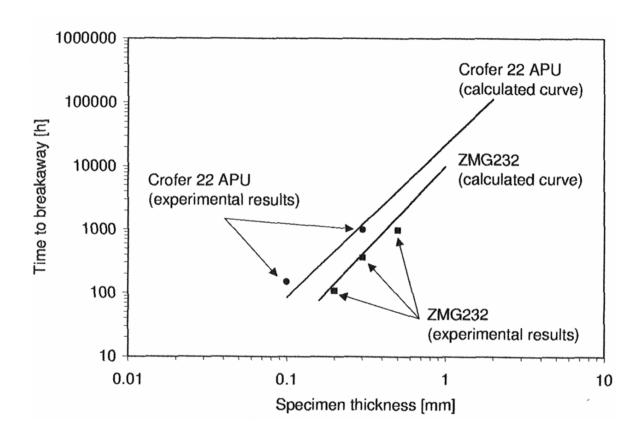


- no oxide spalling
- k_p values for thick specimens breakaway occurs when Cr is reduced to some critical level



- Parabolic rate constants are dependent on specimen thickness
- Possible explanation:
 - Growth stresses in oxide
 - Manganese depletion
 - Minor alloying elements (Si, Ti, Al) internal oxidation with alloy extension

900°C



Correlation of calculated and experimental results considering thickness dependence of $k_{\mbox{\tiny D}}$.